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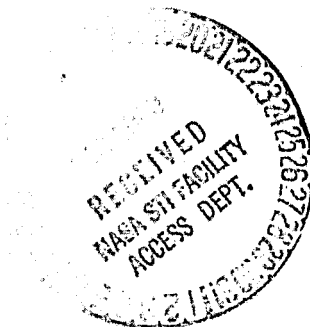
ACCELERATED LIFE TESTING EFFECTS ON CMOS MICROCIRCUIT CHARACTERISTICS

Final Report
May 1976 to December 1979

Contract NAS8-31905

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ABSTRACT

This report covers the time period from May 1976 to December 1979 and encompasses the three phases of accelerated testing: Phase I, the 250°C testing; Phase II, the 200°C testing; and Phase III, the 125°C testing. The duration of the test in Phase I and Phase II was sufficient to take the devices into the wear-out region. The wear-out distributions were used to estimate the activation energy between the 250°C and the 200°C test temperatures. The duration of the 125°C test, 20,000 hours, was not sufficient to bring the test devices into the wear-out region; consequently the third data point at 125°C for determining the consistency of activation energy could not be obtained. It was estimated that, for the most complex of the three device types, the activation energy between 200°C and 125°C should be at least as high as that between 250°C and 200°C. The practicality of the use of high temperature for the accelerated life tests from the point of view of durability of equipment has been assessed. Guidelines for the development of accelerated life-test conditions have been proposed.

The use of the silicon nitride (Si_3N_4) overcoat to improve the high-temperature accelerated life-test characteristics of CMOS microcircuits had been explored in Phase IV of this study. The Phase IV report is attached as an appendix to this report.

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SECTION I

INTRODUCTION

The need for a practical short-term test program, the results of which can be meaningfully interpreted to predict the long-term reliability of CMOS microcircuits, has been recognized. Many months if not years are required to run a life test under conditions reflecting actual applications and requirements of Class A devices. The impracticality of such a test led to the reliance by the industry on long-term reliability predictions based on interpolations of results gathered from accelerated life tests. It is essential to run long (thousands of hours) 125°C life tests to confirm experimentally the validity of such interpolations for CMOS devices. There is a definite possibility that accelerated tests cause the temperature thresholds of a device to be exceeded, thus triggering failure mechanisms unrelated to a device's operation within its specified ratings. The somewhat arbitrary limits established for the use of accelerated life tests must be either experimentally confirmed or revised in accordance with experimental data. The varying complexity of present day CMOS devices should be recognized as a factor in reliability predictions.

SECTION II

OBJECTIVE

The purpose of this program is to determine the consistency of the CMOS microcircuit activation energy in the range of 125°C to 200°C and 200°C to 250°C. Also, this program will determine the relationship of accelerated life-test failures to rated temperature operation and provide a basis for recommendations for accelerated life tests within the scope of the M38510 specifications.

The program encompasses three phases. Phase I is the 250°C accelerated life test, Phase II is the 200°C accelerated life test, and Phase III is the 125°C accelerated life test. In Phases I and II, the objective is to conduct a life test of sufficient duration to generate a minimum of 50 percent cumulative failures. In Phase III, the life test is conducted for 20,000 hours. The collected data is used a) to provide a basis for recommendations of conditions and limits to be used as part of a microcircuit qualification procedure, b) to determine whether any thresholds that could trigger failure mechanisms unique to that temperature are exceeded during the high-temperature testing, c) to assess the usefulness of the 250°C accelerated test as a predictor of long-term reliability.

SECTION III
DEVICE SELECTION

The choice of microcircuit devices for this program was made according to the following criteria:

1. High-reliability Class A devices.
2. Varying degree of complexity representing the product line.
3. Availability.

The following microcircuit types were chosen for this program:

<u>MIL DESIGNATIONS</u>	<u>GENERIC NAMES</u>	<u>FUNCTION</u>
M38510/05001ADX	CD4011A	Two-input quadruple logic NAND gate
M38510/05101ADX	CD4013A	"D"-type flip-flop
M38510/05605ADX	CD4024A	Seven-stage binary counter.

The devices are in flat packs with weldable leads. Solder-dipped leads could not be used at temperatures above the solder melting point. These devices were tested to the individual M38510/50 specifications. Table III of these specifications is attached to this report as Table I (CD4011A), Table II (CD4013A), and Table III (CD4024A). The table specifies the test conditions and limits of the electrical parameters for the group A testing for individual microcircuits. Subgroups 1,2,3,7, and 8 were performed at each measurement point throughout the test program and are the basis for the subsequent data analysis. The CD4011A was tested for functionality under conditions similar to those specified in subgroups 7 and 8 for the other two types.

Further detailed descriptions of these microcircuits are given in Figs. 1 through 7. The figures include photographs of chips with dimensions

shown, magnified photographs with detail visibility, logic diagrams, and circuit diagrams to provide a basis for comparison of the chip sizes and the complexities of the microcircuits involved. Table IV summarizes some of the complexity factors for each microcircuit type.

TABLE III. Group A inspection for device type UL - Continued

Symbol	MIL-STD-883 method	Cases C, D	Terminal conditions and limits												Test limits						Units			
			Q1	Q1	CLK1	RS1	D1	SET1	VSS	SET2	D2	RS2	CLK2	Q2	Q2	VDD	Measured terminal	Subgroup 1 TA = 25°C		Subgroup 2 TA = 125°C		Subgroup 3 TA = -55°C		
																		Min	Max	Min		Max	Min	Max
I _{H1} See note K	3010	75	1	2	15 V	15 V	15 V	15 V	15 V	15 V	15 V	15 V	15 V	15 V	15 V	15 V	All inputs together	8						V
I _{H2}		76 77 78 79 80 81 82 83															CLK1 RS1 D1 SET1 SET2 D2 RS2 CLK2	1.0		45				
I _{L1} See note K	3009	24			GND	GND	GND	GND	GND	GND	GND	GND	GND	GND	GND	GND	All inputs together	-8.0						
I _{L2}		85 86 87 88 89 90 91 92															CLK1 RS1 D1 SET1 SET2 D2 RS2 CLK2	-1.0		-45				
C ₁	3012	93 94 95 96 97 98 99 100			L	L	GND	L	L	L	L	L	L	L	L	GND	CLK1 RS1 D1 SET1 SET2 D2 RS2 CLK2		12					PF

TABLE II - Device: CD4013A, Electrical Test Parameters, (continued)

TABLE III. Group A Inspection for device type D1. -Continued.

Symbol	MIL-STD-883 method	Cases C, D	Terminal conditions and limits										Test limits				
			Symbol	Test No.	Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Subgroup 9 T _A = 25° C	Subgroup 11 T _A = 125° C	Subgroup 11 T _A = -55° C	Duties	
					Q1	Q2	Q3	Q4	Q5	Min	Max	Min					Max
¹ PLH R or S	3003		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
	(Fig 12)		IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
		130	OUT	OUT	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	
		131	OUT	OUT	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	
¹ THL	3004		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
	(Fig 11)		IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
		134	OUT	OUT	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	
		135	OUT	OUT	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	
¹ TLH	3004		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
	(Fig 11)		IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
		136	OUT	OUT	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	
		140	OUT	OUT	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	IN	
¹ CL (max)	(Fig 11)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
	See note P		IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
¹ VIL1	(Fig 11)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
	See note P		IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
tp	(Fig 11)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
	See note Q		IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
¹ SHL	(Fig 13)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
			IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
¹ SLH	(Fig 13)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
			IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
¹ HHL	(Fig 14)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
			IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	
¹ HLH	(Fig 14)		Q1	Q2	Q3	Q4	Q5	Q6	Q7	Q8	Q9	Q10	Q11	Q12	Q13	Q14	
			IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	IN	OUT	

NOTES:

A. Pins not designated may be "high" level logic, "low" level logic or open.

B. Test numbers 17 thru 30 shall be run in sequence.

C. I_{OH} = -0.25 mA at 25° C, -0.175 mA at 125° C, -0.31 mA at -55° C.

D. V_{IH1} = 3.8 V at 25° C; 3.6 V at 125° C; 3.95 V at -55° C.

E. V_{IH2} = 0.5 V at 25° C; 0.25 V at 125° C; 0.75 V at -55° C.

F. I_{OL} = 0.5 mA at 25° C, 0.35 mA at 125° C, 0.65 mA at -55° C.

G. V_{IL1} = 1.1 V at 25° C, 0.8 V at 125° C, 1.5 V at -55° C.

H. V_{IL2} = 2.8 V at 25° C, 2.55 V at 125° C, 3.0 V at -55° C.

I. For input conditions see Figure 9.

J. For input voltage conditions see Figure 10.

K. The device manufacturer may, at his option, measure t_{PL} and t_{PH} at 25° C for each individual input or measure all inputs together.

L. See 4.4.1(c).

M. Test numbers 101 thru 117 shall be run in sequence and the functional tests shall be performed with V_{DD} < 5.0 V and ≥ 15. V.

N. L = 0.5 V minimum and H = 4.5 V minimum.

O. The maximum clock frequency (CL) requirement is considered met if proper output state changes occur with the pulse repetition period set to that given in the limits column.

P. Pulse repetition period = 100 µsec, 50 percent duty cycle. The maximum clock transition time (t_{PL}/t_{PH}/t_{CL}) requirement is considered met if proper output state changes occur with the rise time set to that given in the limits column.

Q. The minimum clock pulse width (t_p) requirement is considered met if proper output state changes occur with the pulse width set to that given in the limits column.

TABLE II - Device: CD4013A, Electrical Test Parameters, (continued)

TABLE III. Group A inspection for device type 05.

Symbol	MIL-STD-883 method	Case C, D	Terminal conditions (pins not designated are open)														Test limits											
			Test No.	1	2	3	4	5	6	7	8	9	10	11	12	13	14	Meas. terminal	Subgroup 1 T _A = 25°C		Subgroup 2 T _A = 125°C		Subgroup 3 T _A = -55°C		Units			
																			Min	Max	Min	Max	Min	Max		Min	Max	
I _{IH}	3010	1	Input	Reset	Q ₇	Q ₆	Q ₅	Q ₄	V _{SS}	NC	Q ₃	NC	Q ₂	Q ₁	NC	V _{DD}	1	1.0	10	10	1.0	1.0	1.0	1.0	µA			
I _{QH}	3010	2	15.0 V	GND	15.0 V												2								µA			
I _{IL}	3009	3	GND	GND													1								µA			
I _{HL}	3009	4	GND	GND													2								µA			
V _{OL2}	3007	5	A	A													A	14.99	14.99	50	50	14.99	14.99	10	mVdc			
V _{OH2}	3007	6	A	A													A	4.20	4.20	500	500	4.20	4.20	500	Vdc			
V _{OH1}	3007	7	B	B													B	4.20	4.20	500	500	4.20	4.20	500	mVdc			
V _{OL1}	3007	8	B	B													B	3.25	3.25	3.25	3.25	3.25	3.25	3.65	Vdc			
V _{ICL}		9	E	E													E	1.50	1.25	1.25	1.25	1.25	1.25	1.75	Vdc			
V _{IF}		10	F	F													F	500	500	500	500	500	500	500	µA			
V _{IS}	3005	11	H	H													7	15 V	15 V						µA			
V _{IS}	3005	12	15 V	15 V													7	15 V	15 V						µA			
C ₁	3012	13	L	L													1	7.0	7.0						PF			
C ₁	3012	14	L	L													2	7.0	7.0						PF			
t _{PHL1}	3003	15	J	GND	G	G	G	G	G	G	G	G	G	G	G	5.0 V	12	0.44	0.55	0.55	0.55	0.55	0.55	0.33	ps			
		16															11	0.88	1.12	1.12	1.12	1.12	1.12	0.66	ps			
		17															9	1.32	1.68	1.68	1.68	1.68	1.68	1.32	ps			
		18															6	1.76	2.24	2.24	2.24	2.24	2.24	1.76	ps			
		19															5	2.20	2.80	2.80	2.80	2.80	2.80	2.20	ps			
		20															4	2.64	3.36	3.36	3.36	3.36	3.36	2.64	ps			
		21															3	3.10	4.00	4.00	4.00	4.00	4.00	3.10	ps			
		22															12	0.44	0.55	0.55	0.55	0.55	0.55	0.33	ps			
		23															11	0.88	1.12	1.12	1.12	1.12	1.12	0.66	ps			
		24															5	1.32	1.68	1.68	1.68	1.68	1.68	1.32	ps			
		25															6	1.76	2.24	2.24	2.24	2.24	2.24	1.76	ps			
		26															5	2.20	2.80	2.80	2.80	2.80	2.80	2.20	ps			
		27															4	2.64	3.36	3.36	3.36	3.36	3.36	2.64	ps			
		28															3	3.10	4.00	4.00	4.00	4.00	4.00	3.10	ps			
t _{THL}	3004	29															J	430	550	550	550	550	550	325	ns			
t _{TLH}	3004	30															I	430	550	550	550	550	550	325	ns			
t _{PHL2}	3003	31	K	K													K	0.97	1.16	1.16	1.16	1.16	1.16	0.66	ps			

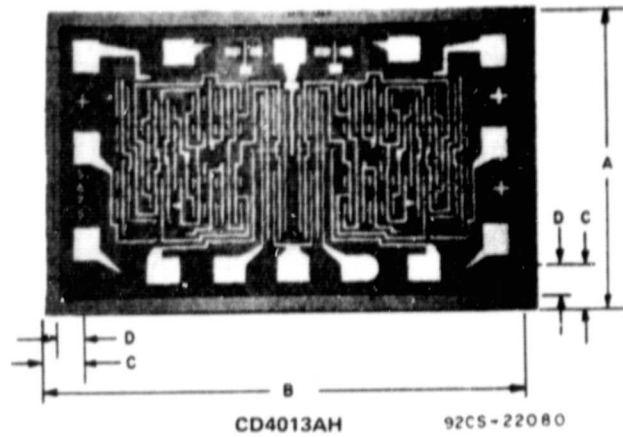
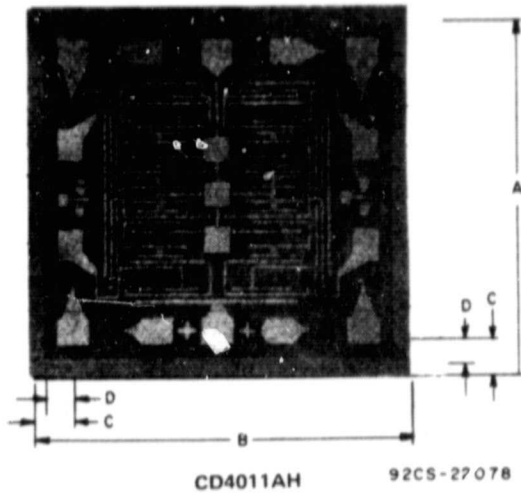
Subgroup 7 Verify truth table, figure 3 @ V_{DD} ≤ 5.0 Vdc and -15.0 Vdc, V_{OL} = V_{SS} + 0.7 Vdc; V_{OH} = V_{DD} - 1.50 Vdc T_A = 25°C.

Subgroup 8 Same test, terminal conditions and limits as subgroup 7, except T_A = 125°C and -55°C.

NOTES:

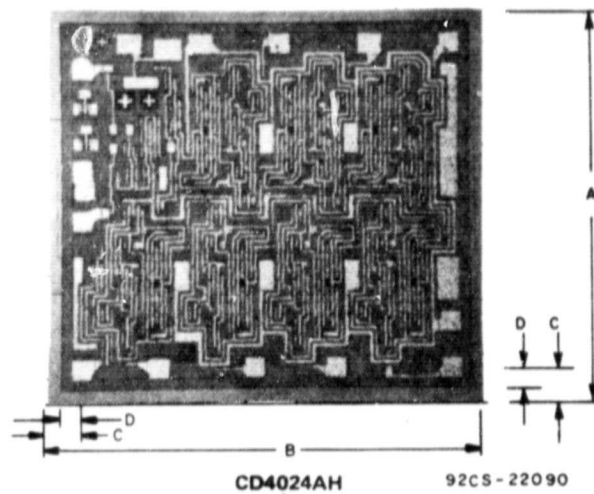
- A. Each output shall be measured using the timing diagram of figure 26.
- B. Each output shall be measured using the timing diagram of figure 26.
- C. I_{IH} = 150 µAdc @ 25°C, -105 µAdc @ 125°C, -165 µAdc @ -55°C.
- D. I_{OL} = 250 µAdc @ 25°C, 175 µAdc @ 125°C, 310 µAdc @ -55°C.
- E. See figure 26 timing diagram.
- F. See figure 29 timing diagram.
- G. Load capacitance C_L = 20 pF.
- H. Check test at each terminal state in 26-F and 26-G. See figure 26.
- I. See figure 41 for test circuit and measurement points.
- J. See figure 42 for test circuit and measurement points.

TABLE III - Device: CD4024A, Electrical Test Parameters



TYPE	A*		B*		C		D		CHIP THICKNESS	
	Mils	Millimeters	Mils	Millimeters	Mils	Millimeters	Mils	Millimeters	Mils	Millimeters
CD4011AH	50 - 58	1.270 - 1.473	53 - 61	1.347 - 1.549	4 - 10	0.102 - 0.254	3.3 - 4.3	0.084 - 0.109	5 - 9	0.127 - 0.228
CD4012AH	50 - 58	1.270 - 1.473	53 - 61	1.347 - 1.549	↕	↕	↕	↕	↕	↕
CD4013AH	41 - 49	1.042 - 1.244	70 - 78	1.778 - 1.981	↕	↕	↕	↕	↕	↕
CD4014AH	79 - 87	2.007 - 2.209	81 - 89	2.058 - 2.260	4 - 10	0.102 - 0.254	3.3 - 4.3	0.084 - 0.109	5 - 9	0.127 - 0.228

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TYPE	A*		B*		C		D		CHIP THICKNESS	
	Mils	Millimeters	Mils	Millimeters	Mils	Millimeters	Mils	Millimeters	Mils	Millimeters
CD4023AH	53 - 61	1.347 - 1.549	53 - 61	1.347 - 1.549	4 - 10	0.102 - 0.254	3.3 - 4.3	0.084 - 0.109	5 - 9	0.127 - 0.228
CD4024AH	73 - 81	1.855 - 2.057	82 - 90	2.083 - 2.286	↕	↕	↕	↕	↕	↕
CD4025AH	49 - 57	1.245 - 1.447	51 - 59	1.297 - 1.498	↕	↕	↕	↕	↕	↕
CD4026AH	89 - 97	2.261 - 2.463	89 - 97	2.261 - 2.463	4 - 10	0.102 - 0.254	3.3 - 4.3	0.084 - 0.109	5 - 9	0.127 - 0.228

* The photographs and dimensions of each COS/MOS chip represent a chip when it is part of the wafer. When the wafer is cut into chips, the

cleavage angles are 57° instead of 90° with respect to the face of the chip. Therefore, the isolated chip is actually 7 mils (0.17 mm) larger in both the A and B dimensions.

Fig. 1 - Dimensions of microcircuit chips.

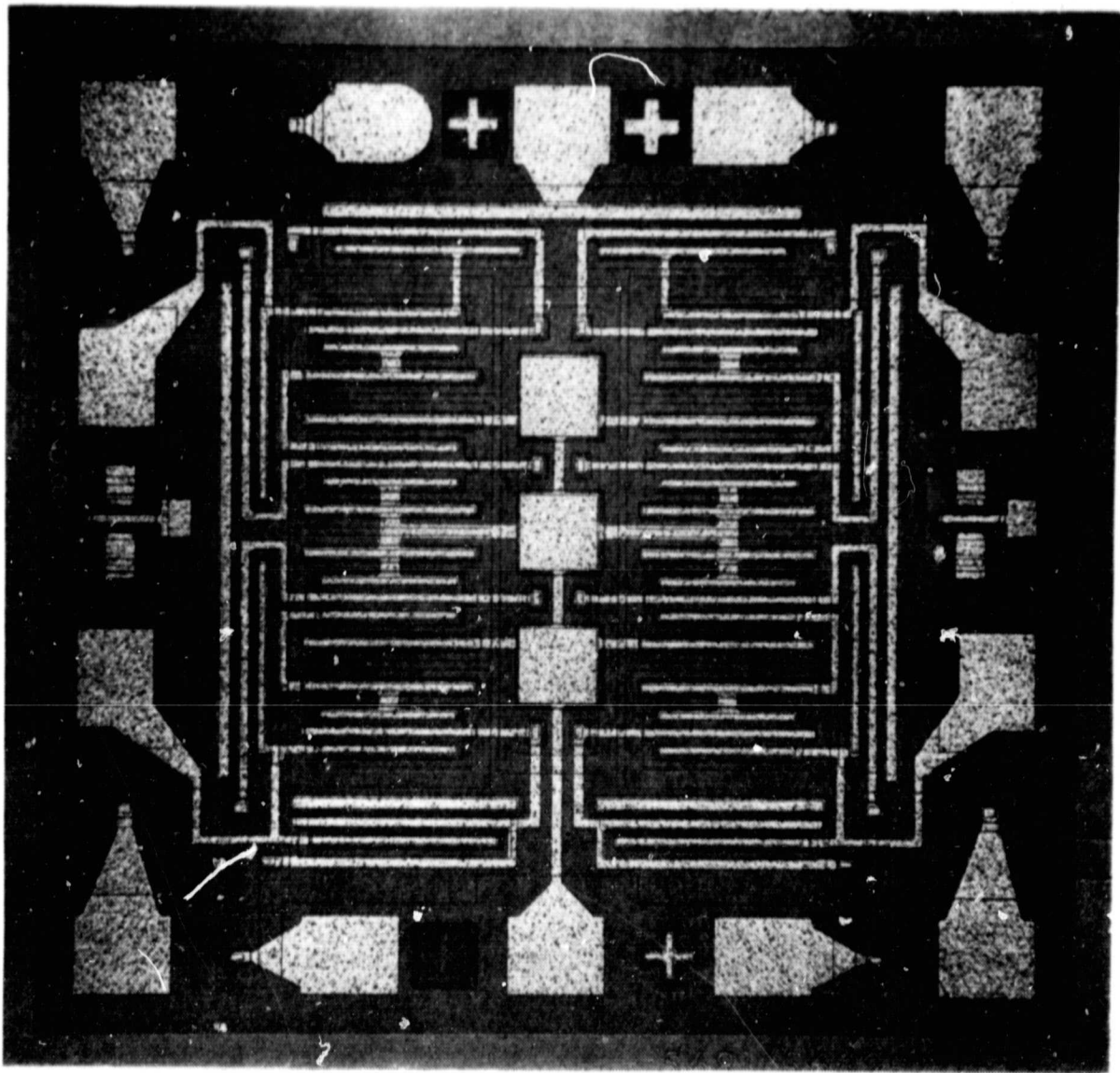


Fig. 2 - CD4011A microcircuit.

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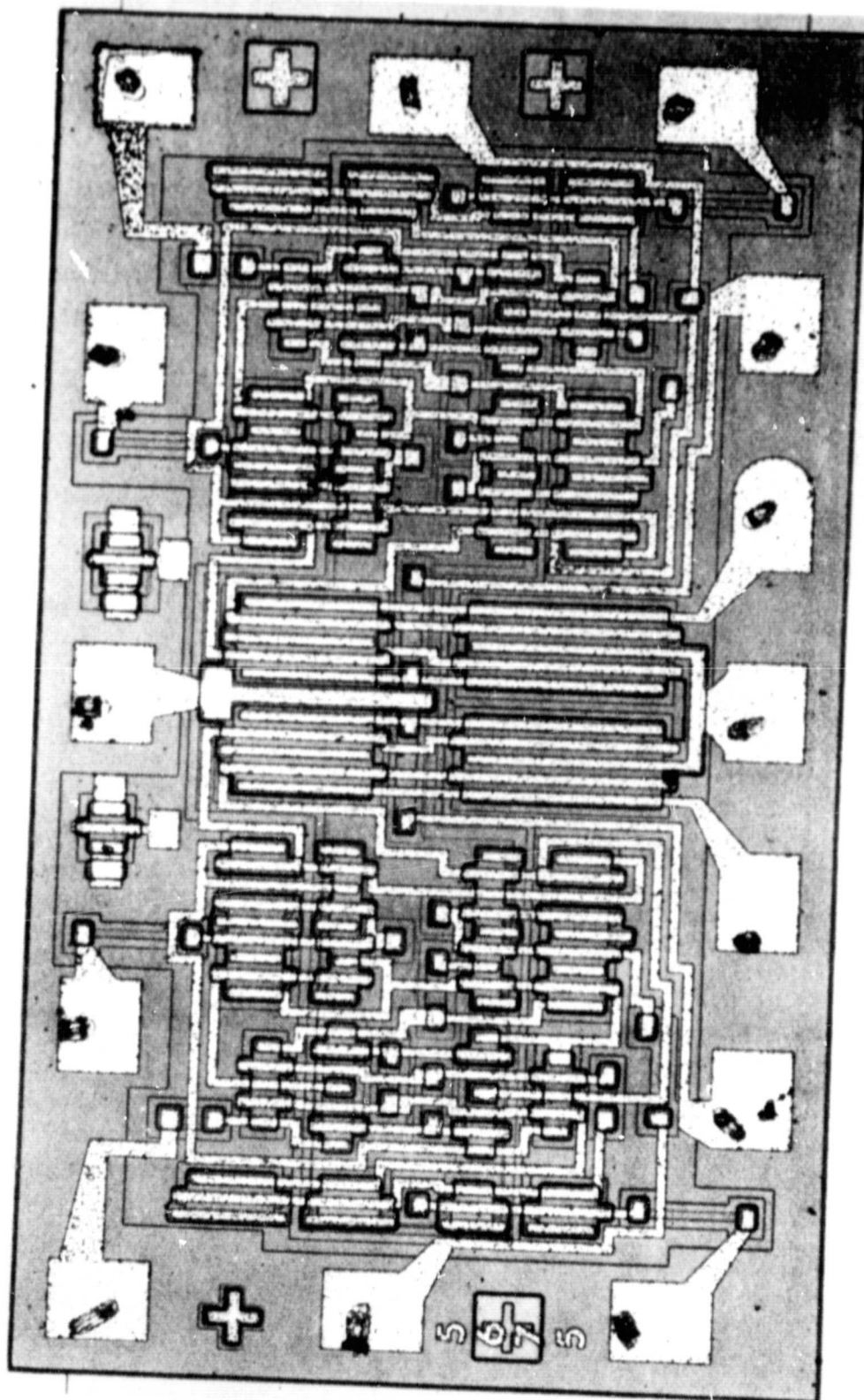


Fig. 3 - CD4013A microcircuit.

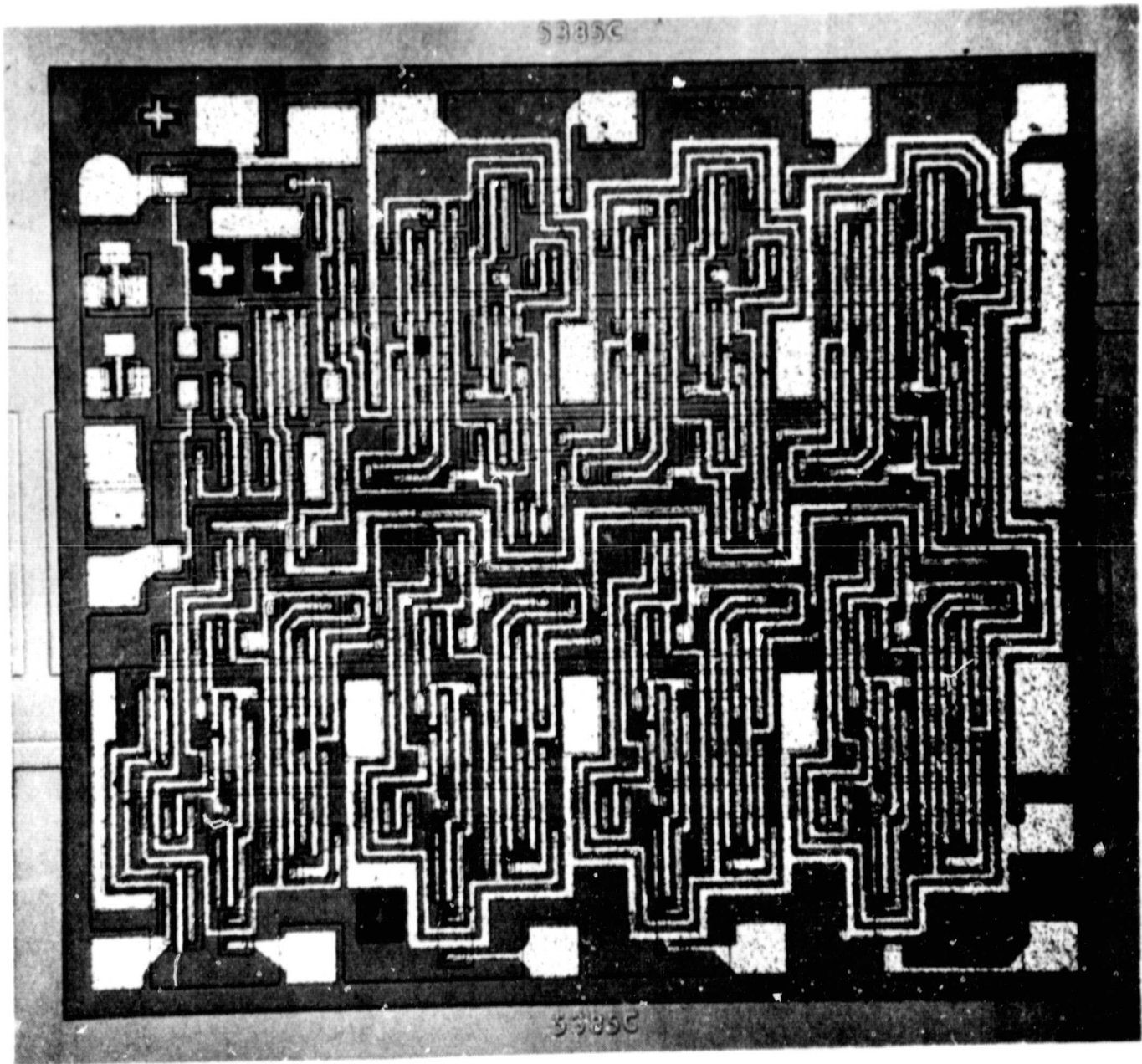


Fig. 4 - CD4024A microcircuit.

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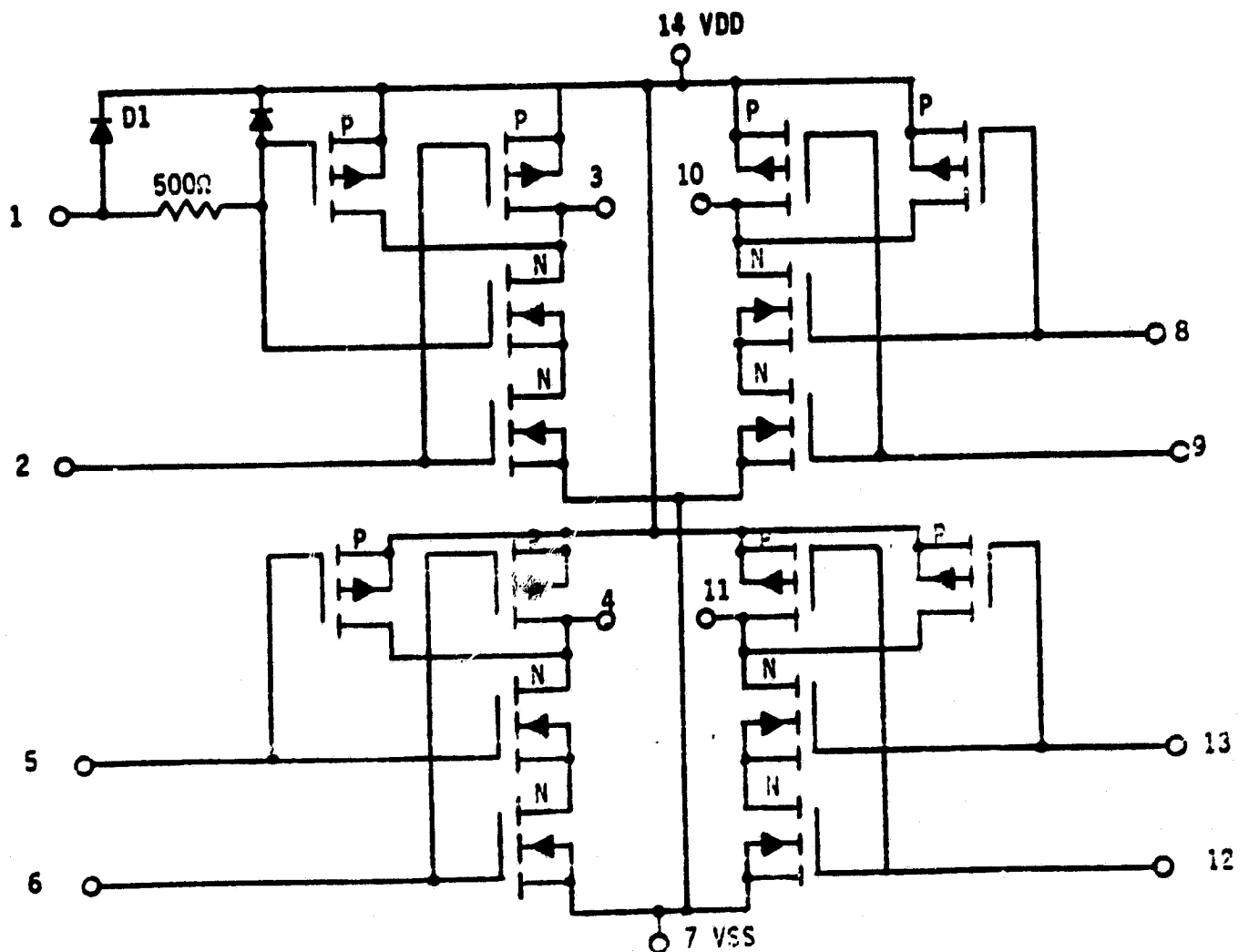
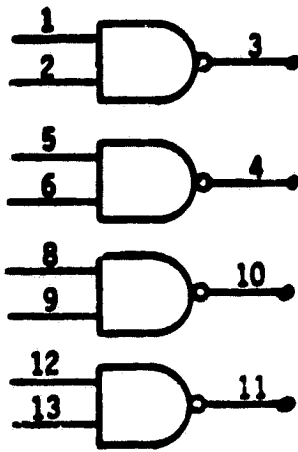


Fig. 5 - Logic and schematic diagrams for the CD4011A.

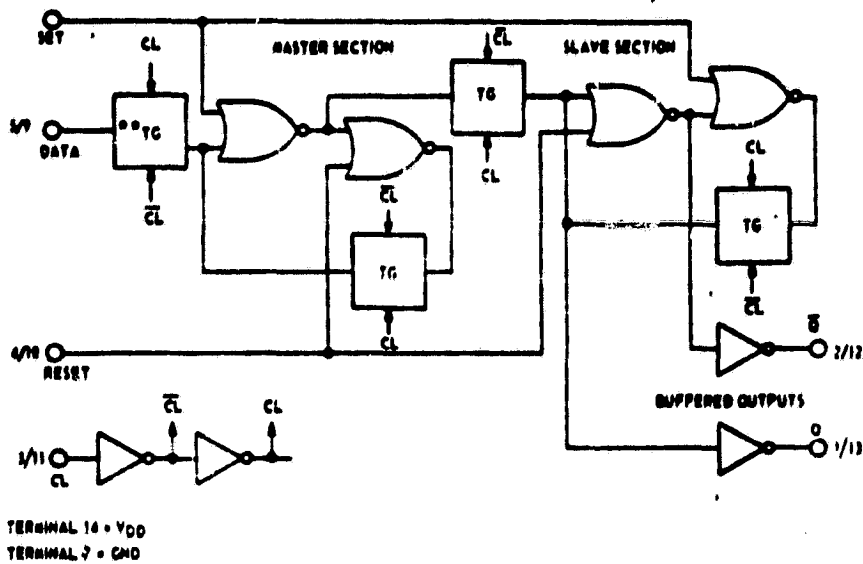


Fig. 6 - Logic diagrams for the CD4013A. (page 1 of 2 pages.)

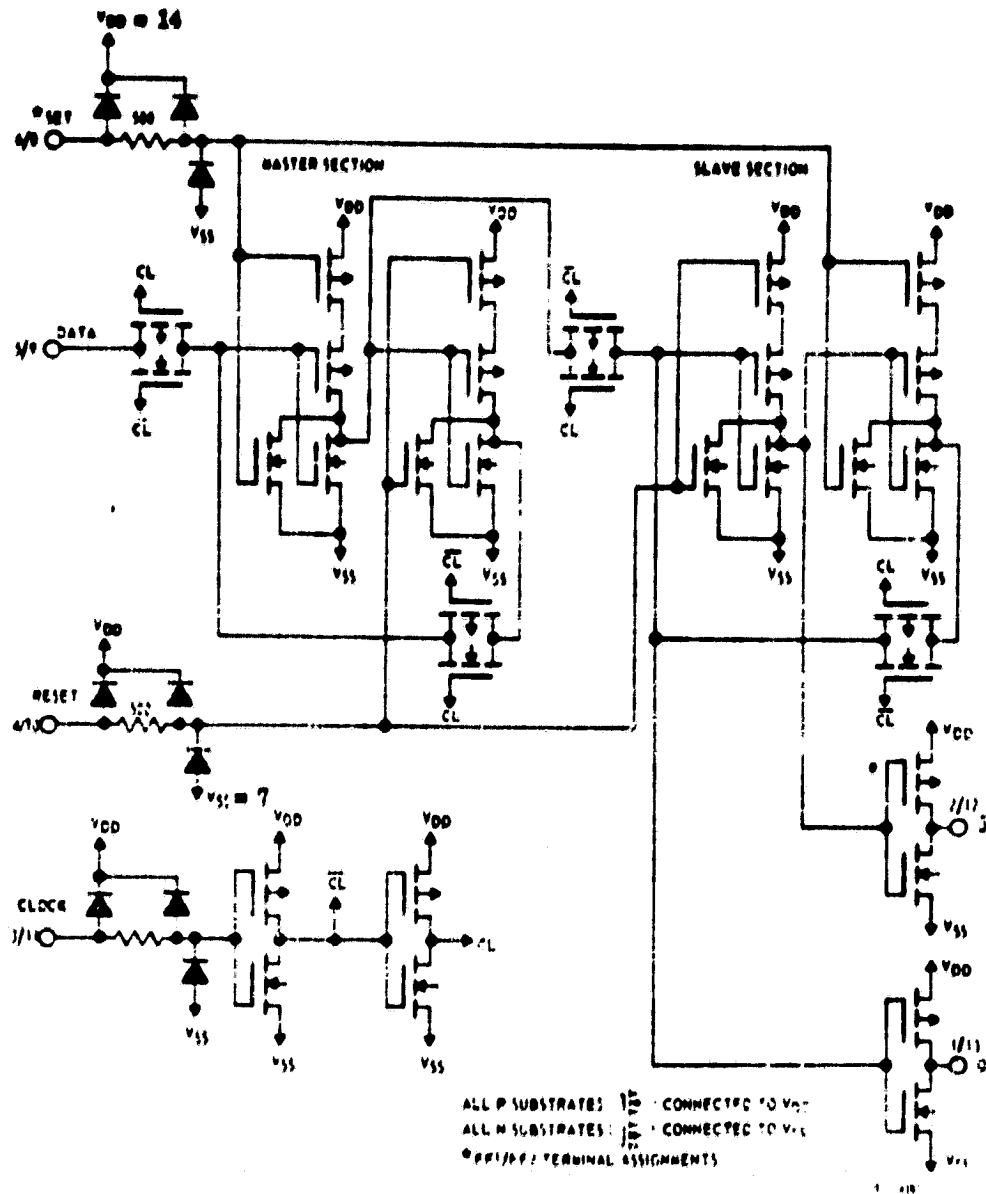


Fig. 6 - Schematic diagrams for the CD4013A. (Page 2 of 2 pages.)

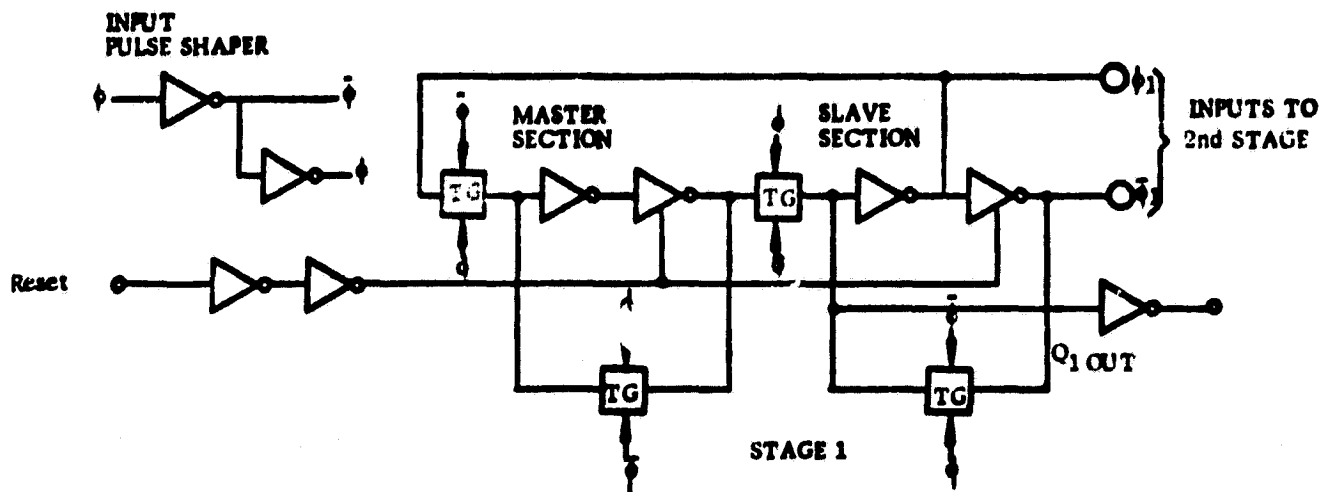
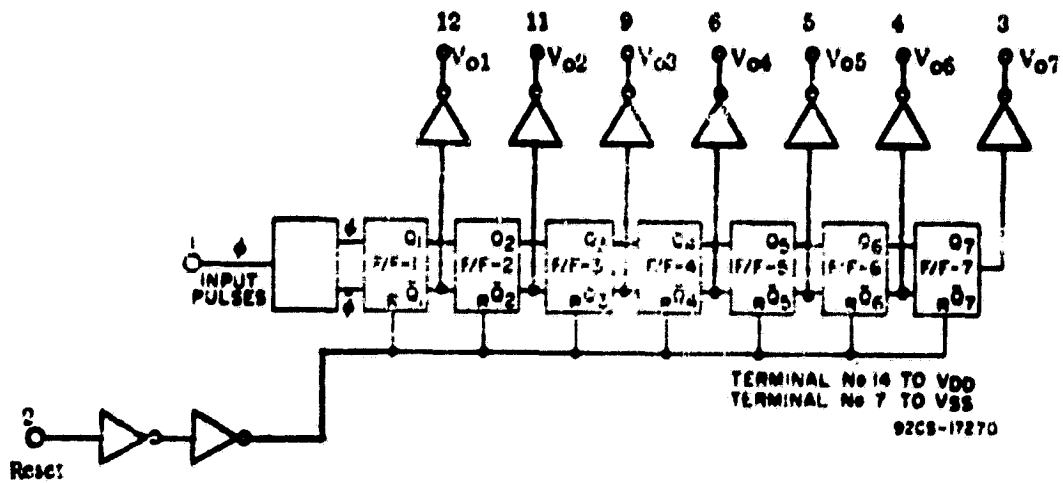


Fig. 7 - Functional and logic diagrams for the CD4024A. (Page 1 of 2 pages.)
 Input Pulse Shaper and one of seven binary stages are shown.

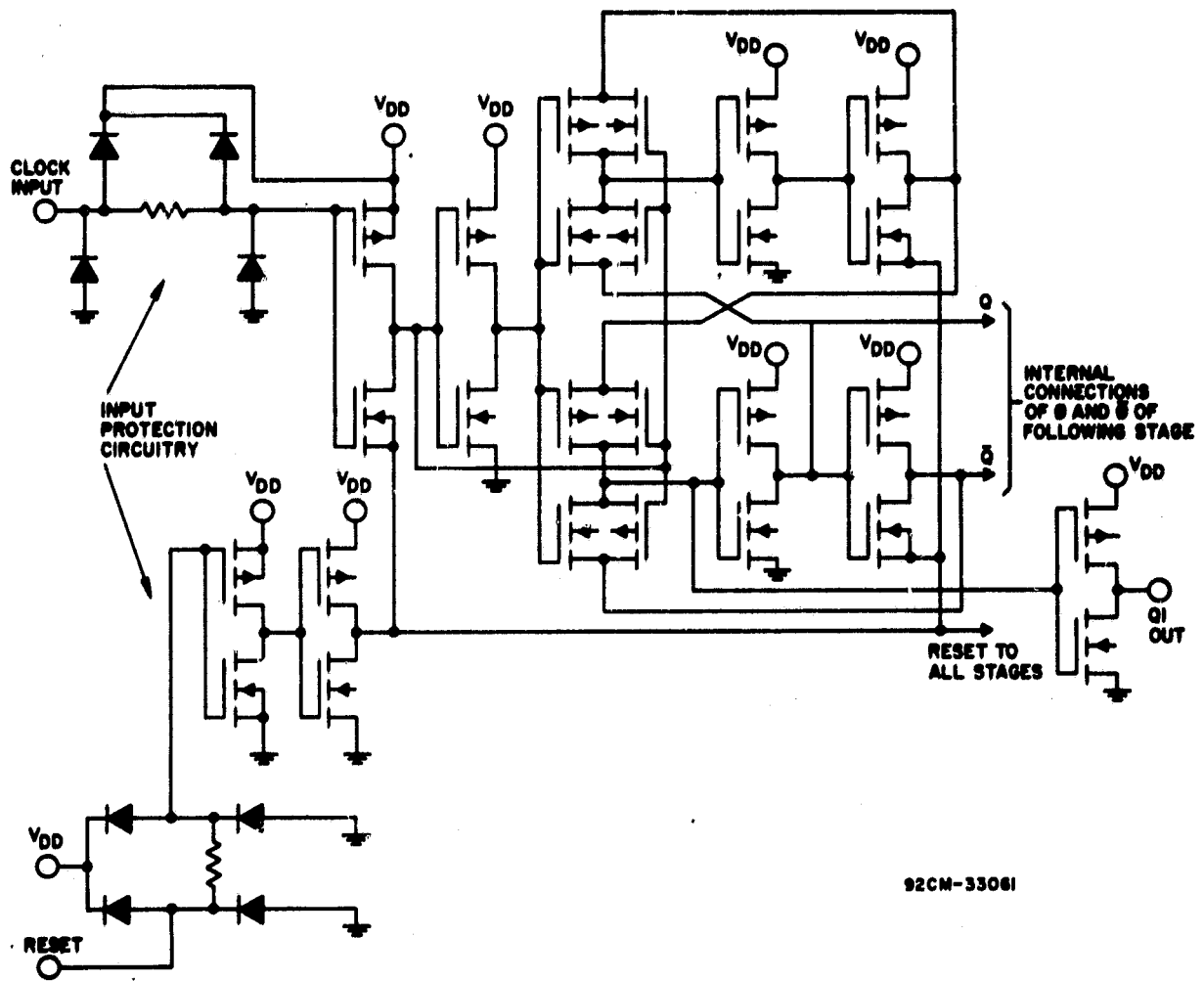


Fig. 7 - Schematic diagram for the CD4024A. (Page 2 of 2 pages.)

Table IV - Microcircuit Complexity Factors

<u>Type</u>	<u>Si Area</u>	<u>No. of Active Elements</u>	<u>Number of Inputs</u>	<u>Number of Outputs</u>
CD4011A	1.9 mm ²	13	8	4
CD4013A	2.1 mm ²	64	8	4
CD4024A	4.2 mm ²	134	2	7

SECTION IV

TEST VOLTAGE AND BIAS

The choice of bias was dictated by the desire to further accelerate the life testing process by stressing the n-channel transistor to possibly the worst-case condition. The available evidence suggests that the n-channel transistor in CMOS microcircuits is the weak link when biased to the off condition (gate is low with respect to drain). The drain-to-source and drain-to-gate potentials set up under this bias accelerate movement of the positively charged (usually sodium) particles. These particles are thought to accumulate in the oxide, thereby neutralizing the effect of the negatively biased gate and setting up a mechanism for potential leakage. The biases used are shown in the pin connection diagrams of Fig. 8. The operating voltage was chosen as 12.5 volts dc to conform to the MIL-M-38510 detail specifications.

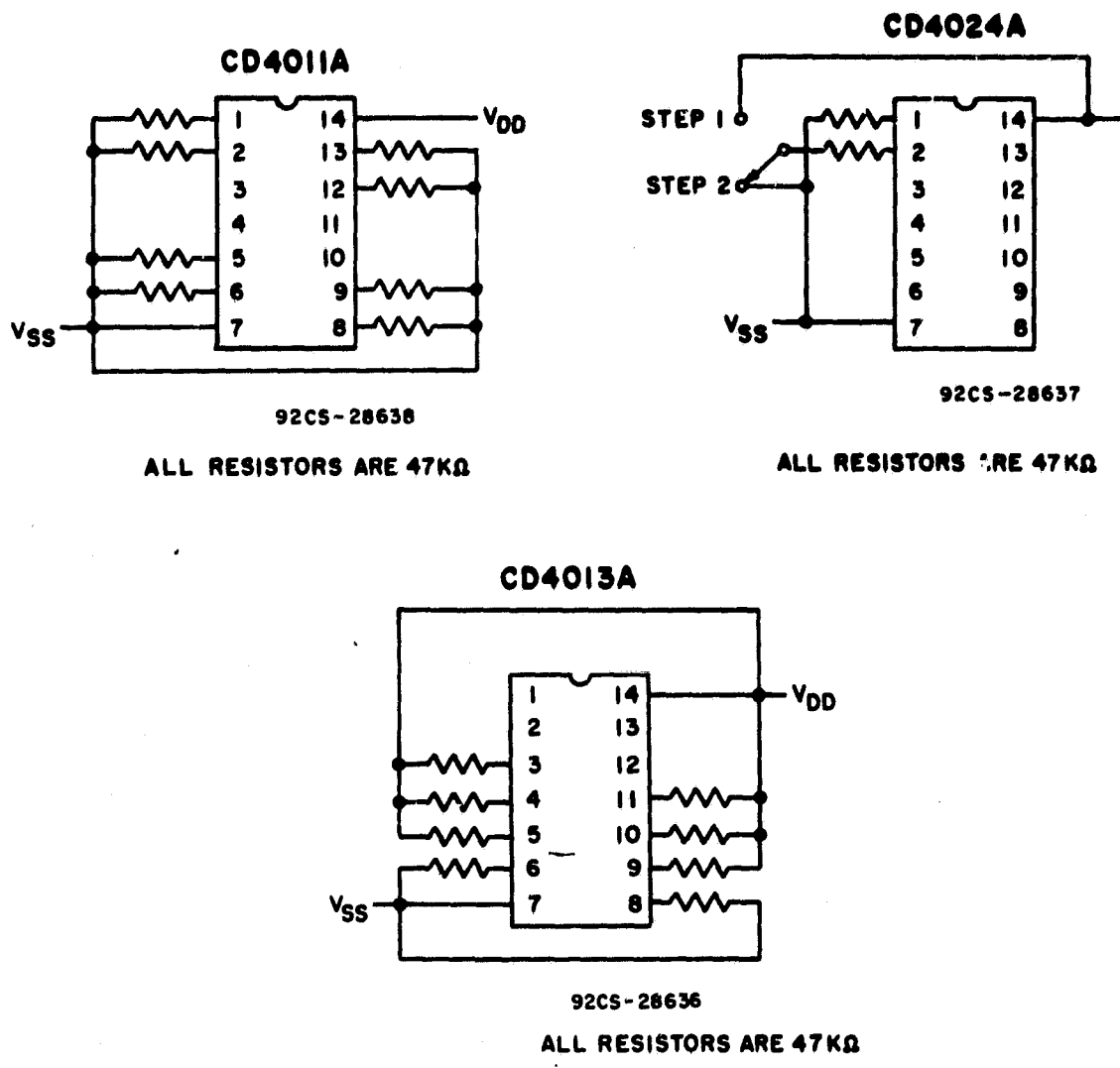


Fig. 8 - Bias connection diagrams.

SECTION V

THE TEST

The test matrix was developed and is shown in Fig. 9. Devices were selected from three lots in each type to represent broad process variations. The program encompasses three life-test temperatures. Each lot is represented by twenty test devices in each life test for a total of sixty test devices of each type. Each test sample of twenty test devices included, in addition, five control devices which were monitored at each measurement point together with the test devices, but were not life-tested.

Prior to the beginning of the contract, trial runs were started. Data from those runs prompted the introduction of more measurement points for the 250°C as well as the 200°C life test. The testing at each measurement point was broadened to include 125°C, and -55°C measurements.

As the final results of the 250°C test became available and the first results of the 200°C tests started to come in, a desirability to evaluate the impact of the manufacturing environment upon the test results was recognized. In order to accomplish this, the high temperature burn-in ovens were transferred from Findlay, Ohio plant to Somerville, N.J. upon the completion of the 200°C test. There were devices left over from some of the lots made for this program. These devices were used to run repeat tests. Two device types: CD4011A and CD4013A were tested at 250°C and 200°C. The task was accomplished by the engineering personnel, and the measurements at down periods were done utilizing Somerville's facilities. These tests were completed at no additional cost to the government.

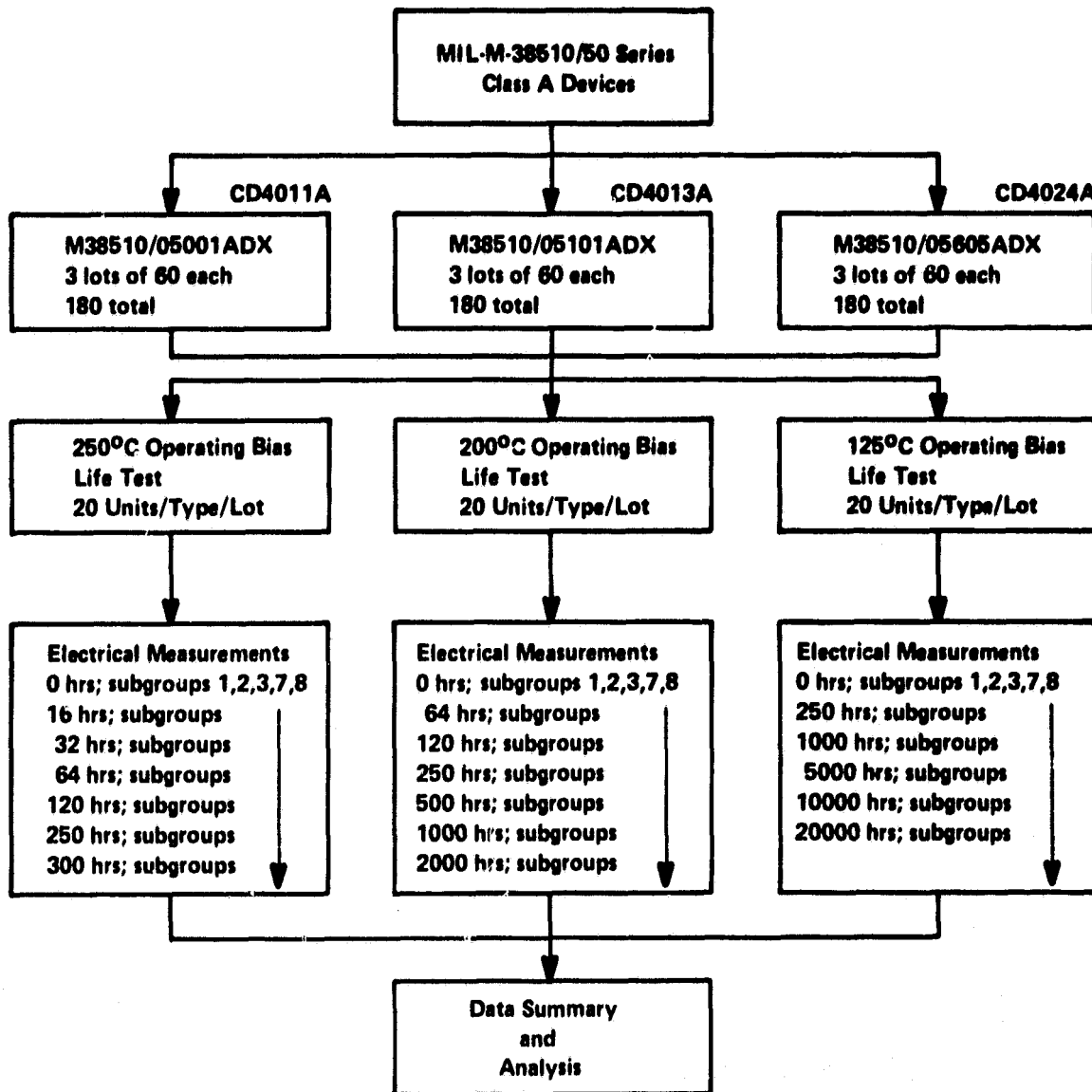


Fig. 9 - Test Matrix.

SECTION VI
DISCUSSION OF TEST RESULTS

Summary of Failure Attributes

The summaries of the failure attributes and cumulative percentage of failures are presented in Tables V-XVII. The results of the 250°C and the 200°C repeat tests are shown in Tables XI-XIV. The sample size does not always remain twenty devices because those devices that were lost due to malfunctioning of the automated test equipment and those which were continuity rejects because of poor socket connections were removed from the count. The data from these tables were then plotted on log normal graph paper to present the cumulative percent of failures versus the test time. Each graph contains the resultant curves from the basic tests at the three test temperatures for each of the three device types, Figs. 10 through 12. The repeat test plots superposed over the basic test plots are shown for the CD4011A and the CD4013A at the 200°C and 250°C test temperatures to demonstrate the degree of repeatability of results for the tests conducted under different environments, Figs. 13 and 14. The curves for the CD4013A and the CD4024A at 250°C test temperatures, Figs. 11 and 12, are continued with dashed lines at the points where the tests have been terminated on one of the three test lots having accumulated at least 50 percent cumulative failures.

The cumulative-failures distributions, as they appear in the graphs of Figs. 10 through 14, strongly suggest that at each test temperature the visible distributions represent portions of the familiar "S" shaped curve which is characteristic of the three regions in the life span of a microcircuit*.

* "Evaluation of Microcircuit Accelerated Test Techniques," Final Technical Report RADC-TR-76-218 for Rome Air Development Center, Griffiss AFB, N.Y., 13441

TABLE V - Summary of Cumulative Failures for Device Type CD4011A

250°C Test

Hours \ Lot No.	16	32	64	120
5361740	0/19	0/19	0/17	16/17
6153050	1/20	6/20	8/20	16/20
6153060	2/20	2/19	7/19	18/19
3-Lot Total	4/59	8/59	15/56	50/56
3-Lot % Failure	7	14	27	89

TABLE VI - Summary of Cumulative Failures for Device Type CD4013A

250°C Test

Hours \ Lot No.	16	32	64
6153080	5/20	7/20	15/15
6123240	2/20	2/20	
5393020	1/20	4/20	
3-Lot Total	8/59	13/60	15/15
3-Lot % Failure	14	36	100

TABLE VII - Summary of Cumulative Failures for Device Type CD4024A

250°C Test

Hours \ Lot No.	16	32	64
6201050	2/20	13/19	
6202230	7/19	10/18	18/18
6201060	3/20	15/20	
3-Lot Total	12/59	38/57	18/18
3-Lot of Failure	20	66	100

TABLE VIII - Summary of Cumulative Failures for Device Type CD4011A

200°C Test

Lot No.	Hours						
	64	120	250	500	750	1500	2000
5361740	0/20	0/20	0/20	0/20	0/20	6/16	11/18
6153050	1/19	1/19	1/19	1/19	1/19	4/19	14/17
6153060	1/19	1/18	1/18	1/18	1/18	6/18	6/18
3-Lot Total	2/58	2/57	2/57	2/57	2/57	16/55	31/53
3-Lot % Failure	3.4	3.5	3.5	3.5	3.5	29	58

TABLE IX - Summary of Cumulative Failures for Device Type CD4013A

200°C Test

Lot No.	Hours				
	64	120	250	500	1000
6153080	0/19	1/17	1/16	3/16	16/16
6123240	0/20	0/18	0/18	0/19	17/19
2-Lot Total	0/39	1/35	1/35	3/35	33/35
2-Lot % Failure	0	2.8	2.8	8.5	94

TABLE X - Summary of Cumulative Failures for Device Type CD4024A

200°C Test

Lot No.	Hours			
	64	120	250	500
6201050	0/20	2/20	11/19	17/19
6202230	0/20	1/20	7/20	17/19
6201060	0/20	0/20	7/20	20/20
3-Lot Total	0/60	3/60	25/59	54/58
3-Lot % Failure	0	5	42	93

TABLE XI - Summary of Cumulative Failures for Device Type CD4011A

250°C Repeat Test

Lot No. \ Hours		Hours					
		16	32	64	96	128	160
5361740	3-Lot Total	1/38	1/38	3/38	3/38	15/38	31/38
6153050							
6153060							
3-Lot % Failure		2.6	2.6	7.9	7.9	39.5	82

TABLE XII - Summary of Cumulative Failures for Device Type CD4013A

250°C Repeat Test

Lot No. \ Hours		Hours				
		8	16	32	48	64
6153080	2-Lot Total	2/38	3/38	5/38	8/38	24/38
6123240						
2-Lot % Failure		5.3	7.9	13	21	63

TABLE XIII - Summary of Cumulative Failures for Device Type CD4011A

200°C Repeat Test

Hours		64	128	250	500	1000	1500	2000	2500
Lot No.									
5361740 6153050 6153060	3-Lot Total	0/38	3/38	4/38	4/38	6/38	7/38	11/38	30/38
3-Lot	% Failure	0	8	11	11	16	18	29	79

TABLE XIV - Summary of Cumulative Failures for Device Type CD4013A

200°C Repeat Test

Hours		64	128	250	500	1000	1500	2000
Lot No.								
6123240		2/38	2/38	2/38	3/38	9/38	19/38	37/38
	% Failure	5	5	5	8	23	50	97

TABLE XV - Summary of Cumulative Failures for Device Type CD4011A

125°C Test

Hours \ Lot No.	168	500	1000	2500	5000	10,000	15,000	20,000
5361740	0/19	0/19	0/18	0/18	0/18	0/18	0/18	0/18
6153050	0/20	0/20	0/18	0/18	0/18	0/17	0/15	0/15
6153060	0/20	0/20	0/20	0/20	1/18	1/18	1/18	1/18
3-Lot Total	0/59	0/59	0/56	0/56	1/54	1/53	1/51	1/51
3-Lot % Failure	0	0	0	0	1.8	1.9	2.0	2.0

TABLE XVI - Summary of Cumulative Failures for Device Type CD4013A

125°C Test

Hours \ Lot No.	168	500	1000	2500	5000	10,000	15,000	20,000
6153080	0/20	0/20	0/20	0/20	0/20	0/20	-	0/20
6123240	0/20	0/20	0/20	0/20	0/20	0/20	-	0/20
5393020	0/20	0/20	0/20	1/20	4/20	4/20	-	4/20
3-Lot Total	0/60	0/60	0/60	1/60	4/60	4/60	-	4/60
3-Lot % Failure	0	0	0	1.7	6.7	6.7	-	6.7

TABLE XVII - Summary of Cumulative Failures for Device Type CD4024A

125°C Test

Hours \ Lot No.	168	500	1000	2500	5000	10,000	15,000	20,000
6202230	0/20	0/20	0/20	2/20	-	2/20	2/20	3/20
6201050	0/20	0/20	2/20	3/20	-	4/20	4/20	4/20
6201060	0/20	0/20	0/20	0/20	-	1/20	2/20	2/20
3-Lot Total	0/60	0/60	2/60	5/60	-	7/60	8/60	9/60
3-Lot % Failure			3.3	8.3		11.7	13.3	15

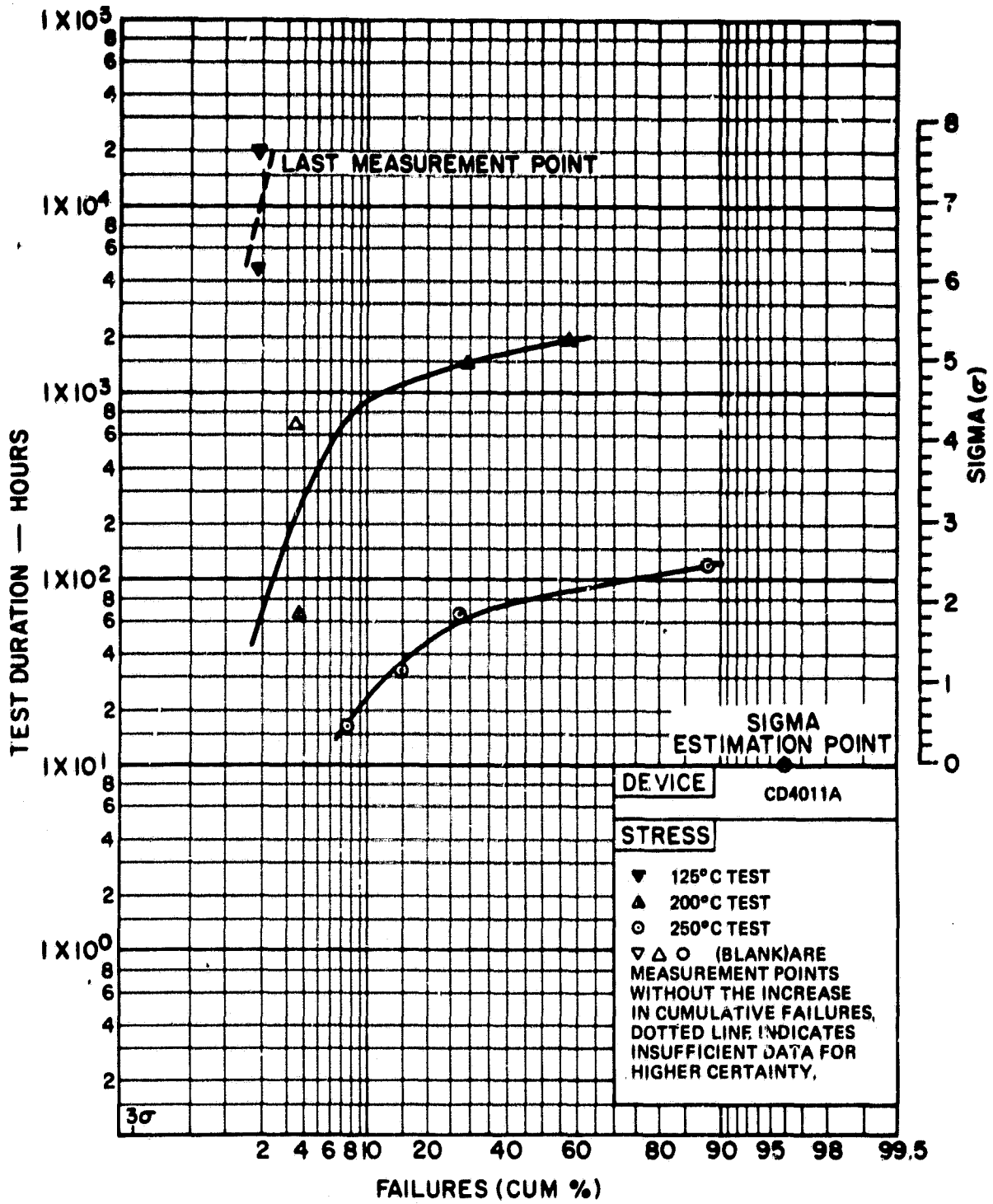


Fig. 10 - Distribution of test failures for CD4011A.

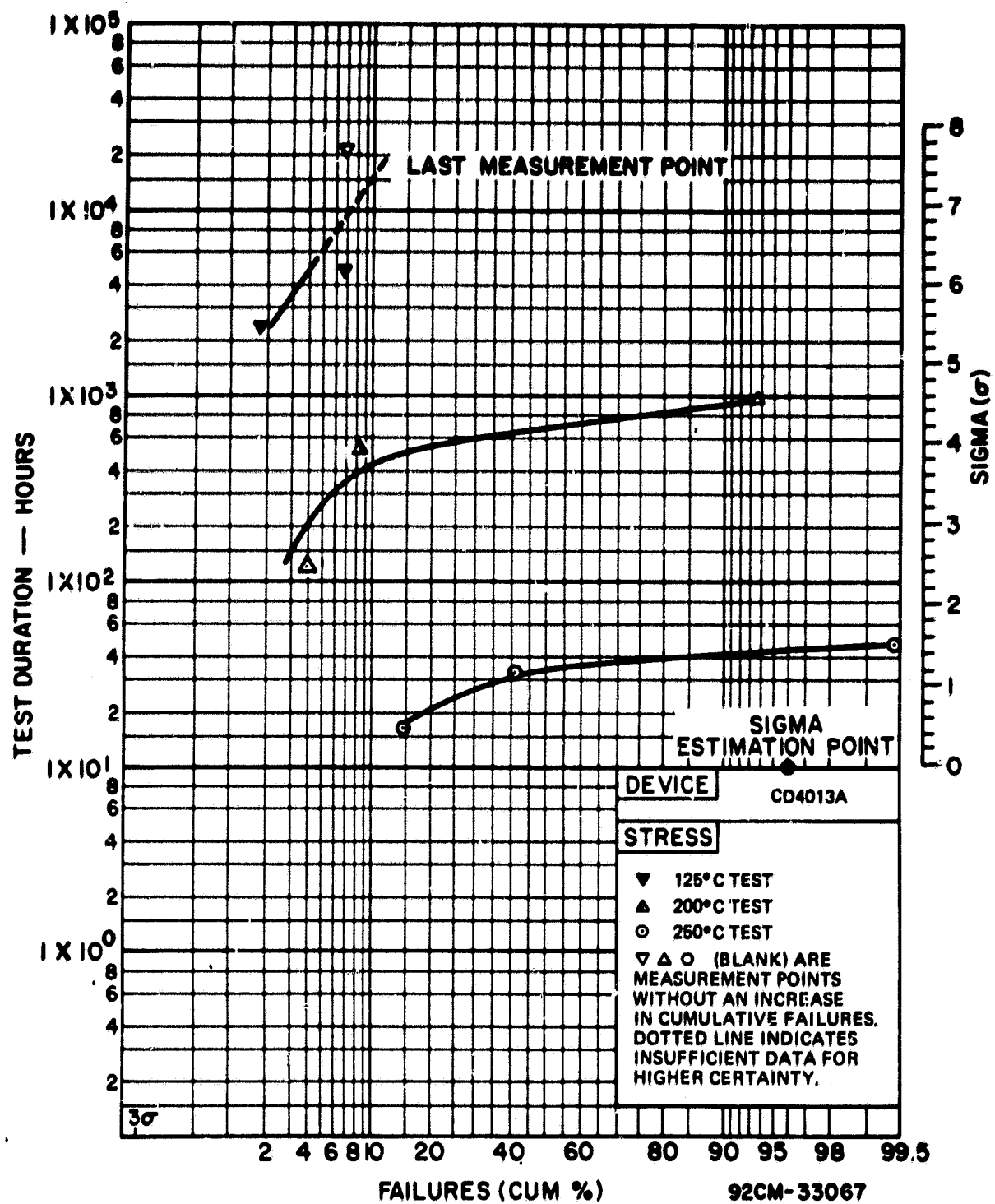


Fig. 11 - Distribution of test failures for CD4013A.

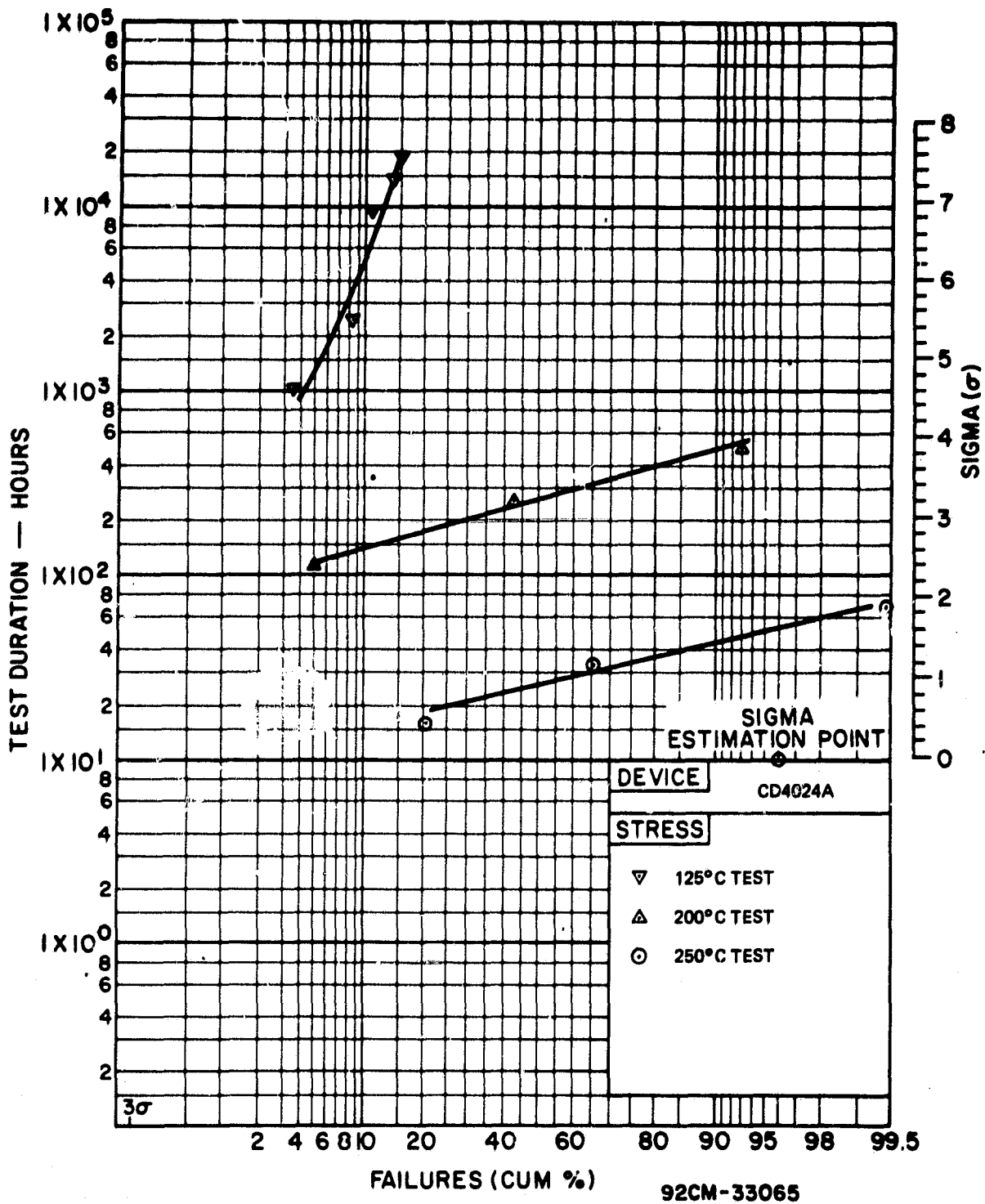
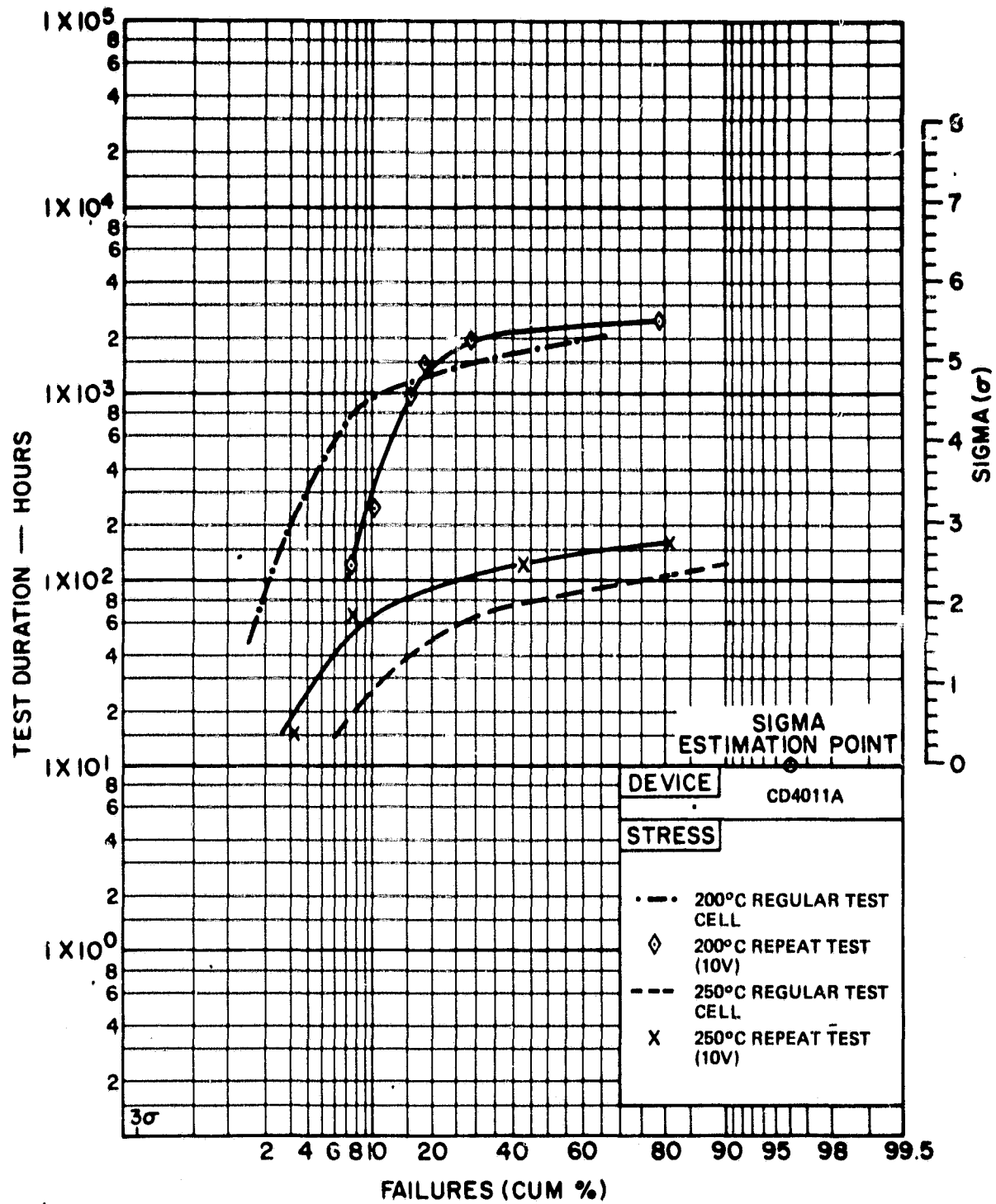


Fig. 12 - Distribution of test failures for CD4024A.



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Fig. 13 - Distribution of test failures for CD4011A - Repeat test.

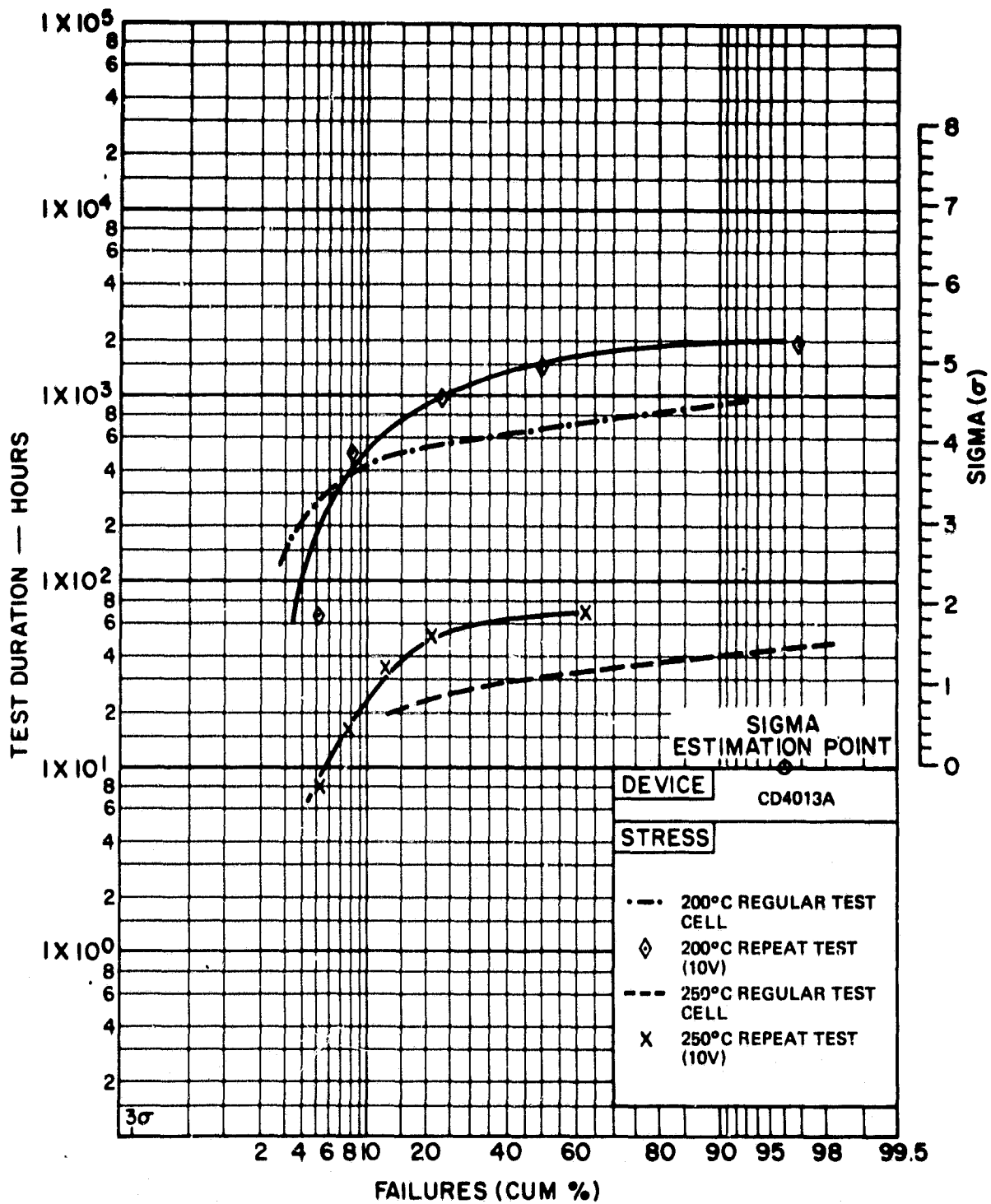


Fig. 14 - Distribution of test failures for CD4013A - Repeat test.

The lower tail regions which represent the early failures (infant mortality) distributions are largely taken out by the standard 125°C burn-ins to which all test devices had been subjected prior to the accelerated life tests. The useful life regions are the regions with constant or decreasing failure rates. These regions are clearly evidenced at 200°C and 125°C test temperatures. The third region shown in the S curve is the wear-out region; this region is represented by the main distribution. The presence of this region is apparent in the 250°C and the 200°C test temperature curves. The characteristic feature of this wear-out region is increasing failure rate. The wear-out region has not been reached by the tests conducted at 125°C.

The 250°C test curves, with a possible exception of the CD4011A, exhibit a compression of the useful life region to such an extent that it becomes indistinguishable from the wear-out region for all practical purposes. Moreover, the available data suggest that the onset of wear-out could have occurred quite early in the test, and that it might have been caused by the exceeding of a yet unknown threshold peculiar to that temperature. Because of these factors it is impossible to estimate the effect of the 125°C burn-ins on the results of accelerated testing at 250°C.

The transition from the useful life region to the wear-out region is most clearly defined by the 200°C test curves for the CD4011A and the CD4013A. The onset of the wear-out region is identified by the knee in the curve where the failure rate begins to increase. The location of this knee is at about 1000 hours for the CD4011A, about 400 hours for the CD4013A, and could be estimated to be at about 100 hours for the CD4024A. The repeat tests (Figs. 13 and 14) conducted at two test temperatures, i.e., 250°C and 200°C, with the CD4011A and the CD4013A, have confirmed a) the existence of fairly well defined regions in the life of the tested microcircuits, i.e., the useful life region and the wear-out region, and b) the location of the knee in the "S" curve, the transition from one region into the other, which is characterized by the changing failure rate from constant to increasing.

It should be noted that the main distribution at both 250°C repeat tests occurs noticeably later than those of the first test. The reason for this was found to be the life-test voltage: 10 volts during the repeat test instead of 12.5 volts due to an inadvertant error in setting up the test in a different location and by different personnel. This error does not, however, diminish the validity of the confirmation of the existence of the main distributions with increasing failure rate.

At the test temperature of 125°C, none of the three tested device types has reached the wear-out region at the last down time of 20,000 hours. It should be noted that two of the three tested lots of the CD4011A as well as two of the three CD4013A lots have had zero cumulative failures at the 20,000-hour down time. With the available data, the existence of the wear-out regions at 125°C can only be surmised.

The importance of identifying the three regions in the life span of a microcircuit lies in the following. The wear-out region is useful in determining the activation energy between various test temperatures, which in turn provides a tool for projecting life at application temperature based on the results of accelerated life-test. The location of this region allows one to locate the "knee", the point of the changing failure rate and the end of the useful life of the device. It is suggested that it is important to locate the "knee" in time as well as to determine the percent cumulative failure at this point. The determination of the MTF, for example, should be done using test results obtained from distributions with sigma common to the use temperature and the accelerated test temperature. The knowledge of the early failure region is helpful in assessing the effectiveness of burn-in schedules.

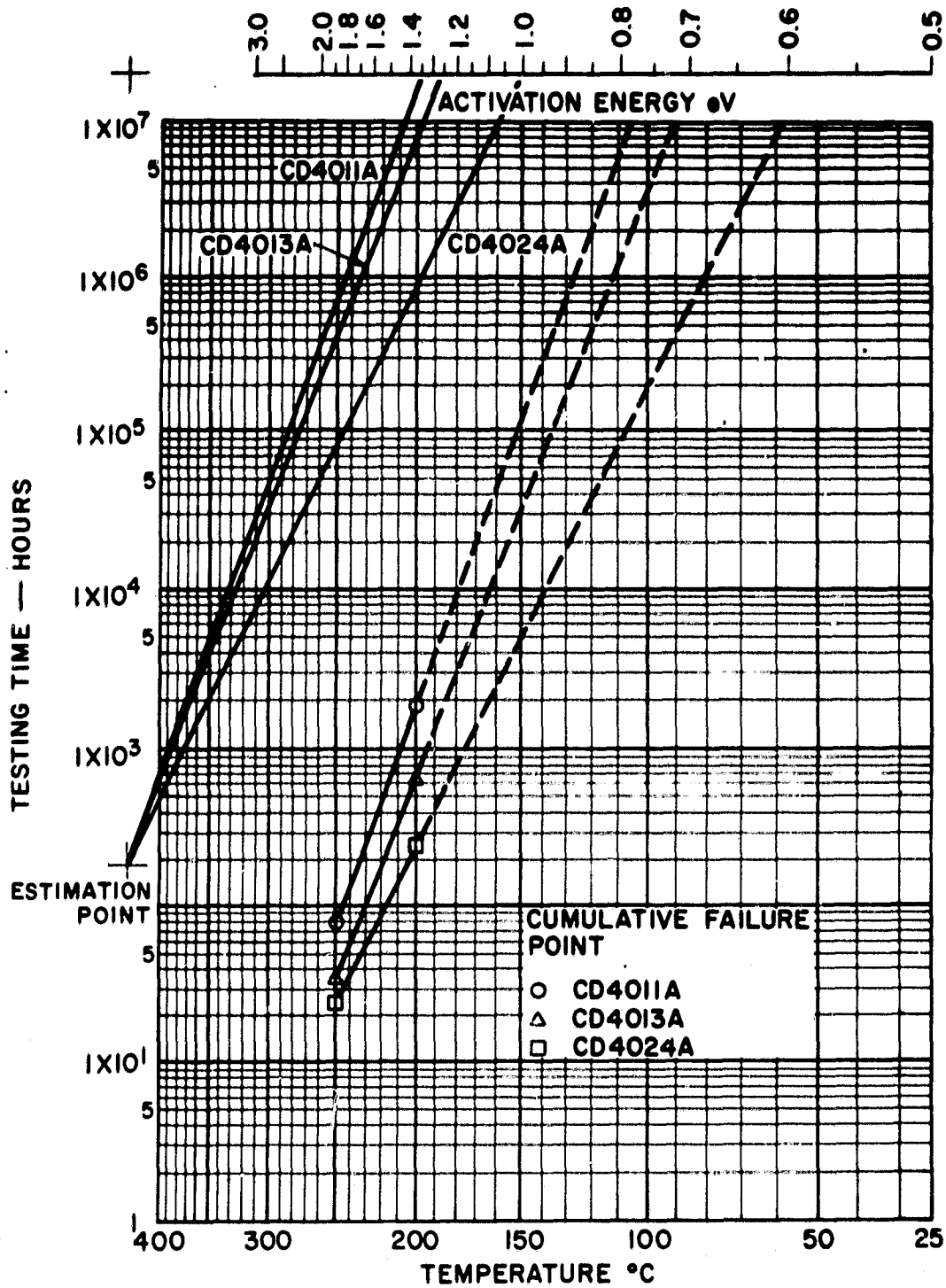
Activation Energy

The activation energy between 200°C and 250°C was estimated on the basis of main distributions (wear-out region); it was found to vary from

type to type: 1.35 eV for CD4011A, 1.25 eV for CD4013A, and 1.0 eV for CD4024A. A more accurate determination of the activation energy and/or verification of the observed type-to-type variations would require a third data point. The wear-out region for the test temperature of 125°C was not reached at 20,000 hours, consequently the third data point was not obtained. The method of graphical estimation of activation energies for each device type is shown in Fig. 15. The times at which 50-percent cumulative failure is reached during tests made on each device type at 200 and 250°C are plotted on the graph of Fig. 15 as a function of temperature, and the resulting points joined by a straight line. Another line with the same slope and passing through the estimation point will intersect the activation energy scale at the value of the activation energy for that device type.

The Effect of Temperature and The Burn-Ins

Prior to the accelerated life tests, all devices were burned-in at 125°C with the standard burn-in schedule for class A CMOS microcircuits: two 24-hour bias burn-ins and one 240-hour dynamic burn-in. It is evident from the 200°C and the 125°C test curves that there were more failures during the early stages of these tests than would be compatible with the constant failure-rate line through the knee, thus indicating decreasing failure rates. These early failures must come from the tail end of the "infant mortality" or "freak" distributions extending into the useful life region. The implications of this finding are that a) the 125°C, 1000-hour life tests presently in use are likely to detect failures which are part of the "infant mortality" distribution when used for lot acceptance, b) the CMOS microcircuits may be inherently more reliable than the results of the 125°C, 1000-hour life tests tend to indicate, and c) better reliability may be realized through improving the burn-ins so that more of the remaining "infant mortality" distribution is removed from the population. It seems impractical, however, to simply extend the duration of the 125°C burn-ins currently in use. Further acceleration of burn-ins by using higher temperature and/or voltage would be suggested for consideration in the development of such burn-ins.



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Fig. 15 - Estimation of activation energy.

Device Complexity

The test results indicate that the "longevity" of a device depends upon the complexity of a device when criticized to MIL-M-38510 electrical end points. The longevity is defined here as the 50-percent failure point, and is located in the wear-out distribution. Of all the factors listed in Table IV, the number of active devices on a chip most closely correlates to the longevity of a microcircuit. Table XVIII summarizes this observation for the 250°C test cell and for the 200°C cell, two temperatures for which 50 percent failure points were reached. This illustration presents a sufficient case against making generalizations when devising acceptance criteria for life test, that is, generalizations based on one technology and applied to another or based on test results of one device type and applied to all device types within the same technology.

Cost Considerations

In the production environment, efficiency and trouble-free operations are extremely important. This study uncovered two problem areas which were the consequence of the high-temperature material used for sockets on the life-test panels and for the device carriers. The material, aromatic copolyester, is extremely brittle. Constant breakage of the life-test sockets necessitated costly repairs and resulted in delays that upset test schedules. Breakage of the very fragile clips that hold devices in carriers resulted in delays in testing as well as in the automated measurements. It was also found that the carriers warp under exposure to 250°C. A warped carrier creates pin-contact problems in test sockets of the automated measuring equipment, and good devices can be rejected as continuity failures. These rejects must be verified by other means of testing, with a resultant loss of time. All these factors contributed significantly to the cost of running the accelerated test. An assessment of the relative cost of running accelerated life tests was made and is presented in Table XIX. All costs are normalized to 125°C for easy comparison.

TABLE - XVIII - Time to 50% Cumulative Failure
Point Versus Complexity of Device

<u>Test Temperature</u>	<u>CD4011A 13 Active Elements</u>	<u>CD4013A 64 Active Elements</u>	<u>CD4024A 134 Active Elements</u>
250°C	80 hrs.	33 hrs	25 hrs
200°C	1800 hrs	650 hrs	250 hrs

TABLE XIX

RELATIVE COSTS

High Temperature Facilities

<u>Factors</u>	<u>Temperature</u>		
	<u>125° C</u>	<u>200° C</u>	<u>250° C</u>
Oven Cost	1	1	1.25
Socket Cost	1	2	7.5
Socket Life	1	1	2.5
Oven Life	1	2	2
Maintenance	1	1.25	1.5
Total	1	5	70

SECTION VII

FAILURE ANALYSIS

CD4011A - The most prevalent type of failure is the loaded output voltage, followed closely by the input leakage. These two most common types of failure, depending upon the severity (amount of deviation from the norm), may result in an eventual functional failure.

CD4013A - The most prevalent types of failure are the total leakage (Iss) and the input leakage. Again, depending upon the severity of the leakage, it may eventually result in a functional failure. The ten Iss tests specified by the MIL-M-38510 detail specification representing different states of the flip-flop do not appear as failures with the same frequency. States which have clock input "high" exhibit more frequent Iss failures than do other states. The "D" input tends to have more frequent input leakage failures than other inputs.

CD4024A - The most prevalent type of failure is the total leakage (Iss). All nine Iss tests except one show equal frequency of occurrence. The ninth test (input and reset are high) exhibits considerable lower frequency of occurrence.

Tables XX, XXI, and XXII give for the 250°C test cell the means, the standard deviation, and the high value at each measurement point on the per lot basis for the surviving devices at two measurement temperatures, 25°C and 125°C. Figs. 16, 17, and 18 represent plots of mean averaged over three lots for each type and at two temperatures. The surviving units are defined as those for which the readings did not reach the clamped values. Clamped values are the upper limits of the instrument range to which the automated measurement system is set.

TABLE XX - I_{ss} Trend with Time for the M38510/05001ADX (CD4011A)

Time		0 Hrs.			16 Hrs.			32 Hrs.			64 Hrs.			120 Hrs.			
Lot #	Test #	50	51	52	50	51	52	50	51	52	50	51	52	50	51	52	
	Unit	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	
25°C Measurements	5361740	Mean	0.17	0.16	0.44	0.75	1.1	2.7	0.83	1.07	1.39	1	1.04	1.27	0.68	10.8	0.37
		S.D.	0.27	0.36	0.69	0.25	0.76	0.19	0.18	0.13	0.17	0.20	0.09	0.33	0.3	30.8	0.32
		H.V.	0.7	1	1.3	1.1	1.1	3	1.2	1.2	1.6	1.4	1.3	1.5	159.8	108.4	1.2
	6153050	Mean	0.65	1.01	1.37	2	1.32	3.4	3.73	3.22	5.55	3.55	3.48	5.21	2.2	1.76	0.70
		S.D.	0.4	0.1	0.16	2.2	0.44	0.56	6.31	1.28	7.87	2.3	0.91	3.8	2.89	1.19	0.14
		H.V.	1.2	1.2	1.7	3.1	3.1	5.6	30.4	8.2	38	11.8	6.3	19.7	10.8	3	0.9
	6153060	Mean	0.07	0.88	1.13	0.9	1.4	3.4	0.67	1.2	1.55	1.61	1.93	2.23			
		S.D.	0.09	0.1	0.12	1.2	1.1	2.3	0.35	0.32	0.34	0.78	0.54	0.75			
		H.V.	0.2	1	1.4	5.7	5.5	12.5	1.2	2	2.5	3.5	3.1	4.7			
125°C Measurements	5361740	Unit	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	
		Mean	100.2	67	74	125.7	100.3	72.1	131.7	96.9	73.4	134.6	89.8	72.8	301.4	457.5	115
		S.D.	19.6	39.7	16	26.4	19	14.6	28.4	20	15	33.4	23.5	15.6	361.1	415.1	24.4
		H.V.	136	109	98	172	132	97	188	137	103	193	133	104	1393	751	158
	6153050	Mean	143.7	64.1	126.2	175.1	103.8	130	180.1	97.1	125.2	196.1	89.1	230.8	259	395.2	103.6
		S.D.	53.3	36.6	31	47.7	26.2	36.5	53	17.6	39.7	60.4	22.8	295.2	137.1	509.2	30.8
		H.V.	222	103	197	265	124	197	284	125	200	292	117	1086	499	227	176
	6153060	Mean	63	79.6	51.3	76.7	79.3	48.5	77.1	78.6	49	45	42.8	27.7			
		S.D.	26	26.4	18.5	28	25.1	19.8	30.1	25.7	19.22	21	18.2	15.3			
		H.V.	138	140	91	134	136	84	132	136	83	86	80	55			

S.D. - Standard deviation

H.V. - High value

Low values were zero

TABLE XXI - I_{SS} Trend with Time for the M38510/05101ADX (CD4013A)

Time		0 Hrs.			16 Hrs.			32 Hrs.			64 Hrs.			120 Hrs.	
Lot #	Test #	50	55	60	50	55	60	50	55	60	50	55	60		
	Unit	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA		
25°C Measurements	5393020	Mean	0.0	0.0	0.0	1.1	0.8	1.4	0.0	0.0	0.5				
		S.D.	0.0	0.0	0.0	4.6	0.8	1.0	0.0	0.0	1.0				
		H.V.	0.0	0.0	0.0	20.0	3.0	3.0	0.0	0.0	3.0				
	6123240	Mean	0.0	0.0	0.0	0.0	0.5	1.2	0.0	0.0	0.1				
		S.D.	0.0	0.0	0.0	0.0	0.8	1.1	0.0	0.0	0.2				
		H.V.	0.0	0.0	0.0	0.0	3.0	3.0	0.0	0.0	1.0				
	6153080	Mean	0.0	0.0	0.0	0.8	1.6	2.0	41.0	87.0	95.0	31.0	3.1-8	3.9-8	
		S.D.	0.0	0.0	0.0	2.4	2.6	2.6	140.0	360	390.0	89.0	1.1-7	1.3-7	
		H.V.	0.0	0.0	0.0	7.0	11.0	11.0	570.0	1500	1600	330	4.4-7	5.0-7	
125°C Measurements	5393020	Unit	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	μA	
		Mean	0.093	0.07	0.092	0.27	0.12	0.19	0.67	2.5	2.4				
		S.D.	0.013	0.015	0.013	0.65	0.71	0.013	2.5	3.5	2.8				
	6123240	H.V.	0.12	0.12	0.12	3.0	0.13	0.14	11.0	13.0	8.2				
		Mean	0.11	0.12	0.12	0.28	0.19	0.21	0.08	11.0	0.13				
		S.D.	0.01	0.009	0.01	0.75	0.36	0.46	0.02	0.08	0.1				
	6153080	H.V.	0.13	0.13	0.13	3.5	1.7	2.2	0.13	0.42	0.52				
		Mean	0.072	0.074	0.074	0.24	0.57	0.64	0.84	0.5	0.53	0.58	0.28	0.35	
		S.D.	0.009	0.007	0.008	0.54	1.2	1.4	2.4	1.1	1.2	0.61	0.41	0.5	
		H.V.	0.09	0.09	0.09	2.3	4.5	5.4	9.1	3.5	3.8	1.6	1.1	1.3	

S.D. - Standard deviation

H.V. - High value

Low values were zero

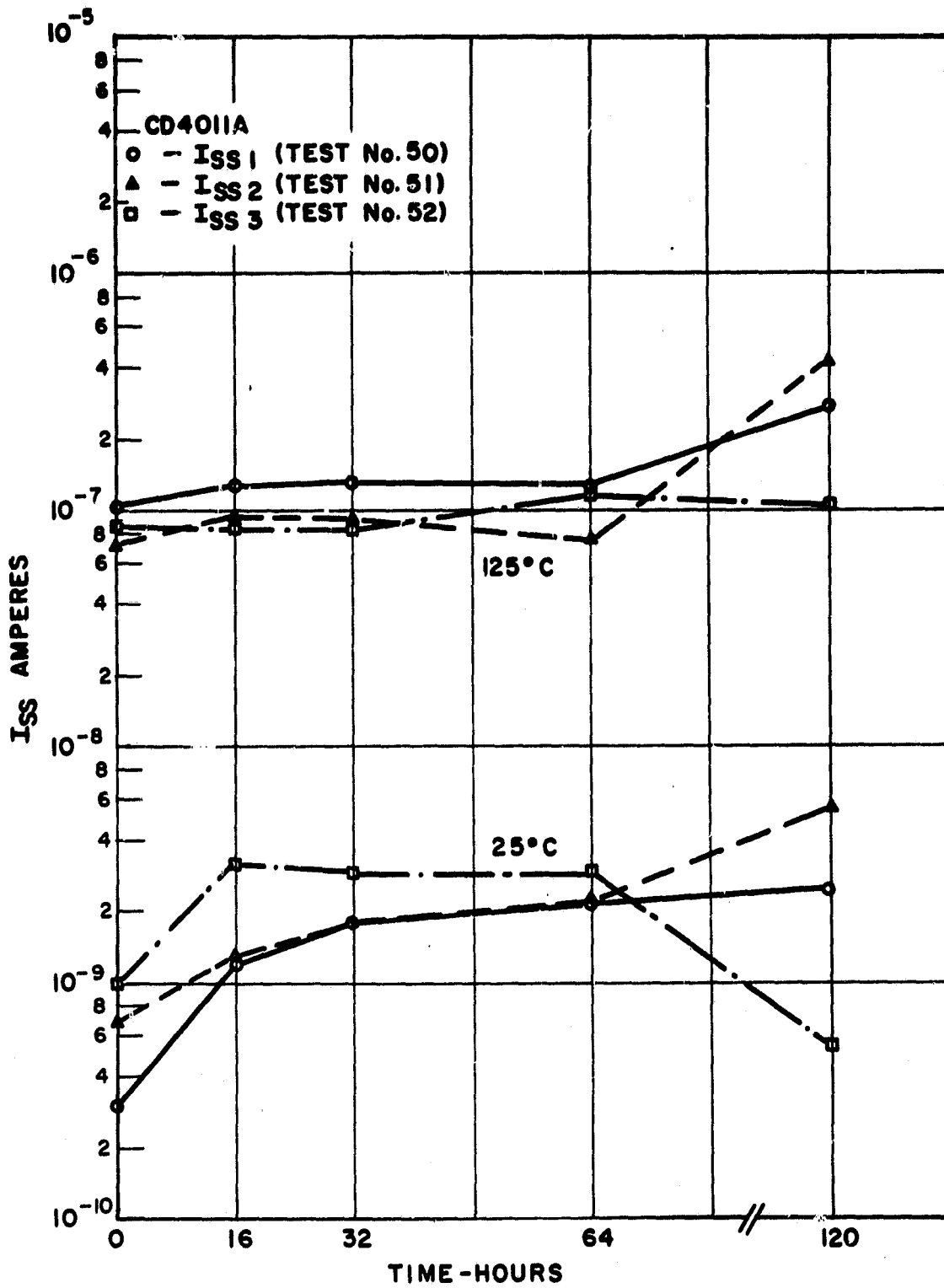
TABLE XXII - I_{gg} Trend with Time for the M38510/05805ADX (CD4024A)

Time		0 Hrs.			16 Hrs.			32 Hrs.			64 Hrs.			120 Hrs.	
Lot #	Test #	60	63	67	60	63	67	60	63	67	60	63	67		
	Unit	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA	nA		
25°C Measurements	6201050	Mean	45.81	53.35	55.8	33.4	35.7	34.2	41.7	103.7	82.3				
		S.D.	109.36	110.98	110.57	129	125.2	123	96.6	246.3	177.5				
		H.V.	418	417	418	565	564	555	578	580	565				
	6201060	Mean	1.11	3.35	2.88	0	9.6	8.75	11	12	12				
		S.D.	1.11	2.39	2.86	0	0.7	1.9	24	24	23				
		H.V.	4	11	13	0	11	16	114	113	112				
	6202230	Mean	2.31	4	2.25	1.42	10.85	8.4	20	20	17.2	782	779	761	
		S.D.	5	5.63	1.1	5.95	6	0.95	29	27.8	26.1	287	285	293	
		H.V.	23	27	4	26	37	9	99	103	101	1160	1153	1142	
125°C Measurements	6201050	Unit	μ A	μ A	μ A	μ A	μ A	μ A	μ A	μ A	μ A	μ A	μ A	μ A	
		Mean	0.42	0.54	0.54	0.70	0.77	0.73	1.2	1.2	1.9				
		S.D.	0.61	0.83	0.83	1.86	1.89	1.84	1.7	1.7	1.4				
		H.V.	2.34	2.96	2.95	8.4	8.41	8.41	6.03	5.76	5.24				
	6201060	Mean	0.18	0.21	0.21	0.17	0.19	0.18	3	3	3				
		S.D.	0.06	0.10	0.10	0.06	0.11	0.12	5	4	4				
		H.V.	0.37	0.55	0.56	0.29	0.28	0.28	0.5	0.49	0.50				
	6202230	Mean	0.12	0.12	0.12	0.24	0.22	0.22	0.45	0.44	0.43	7.58	All clamped		
		S.D.	0.02	0.02	0.02	0.29	0.27	0.27	0.50	0.48	0.47	2.75			
H.V.		0.2	0.21	0.21	1.4	1.35	1.32	1.7	1.7	1.6	9.39				

S.D. - Standard deviation

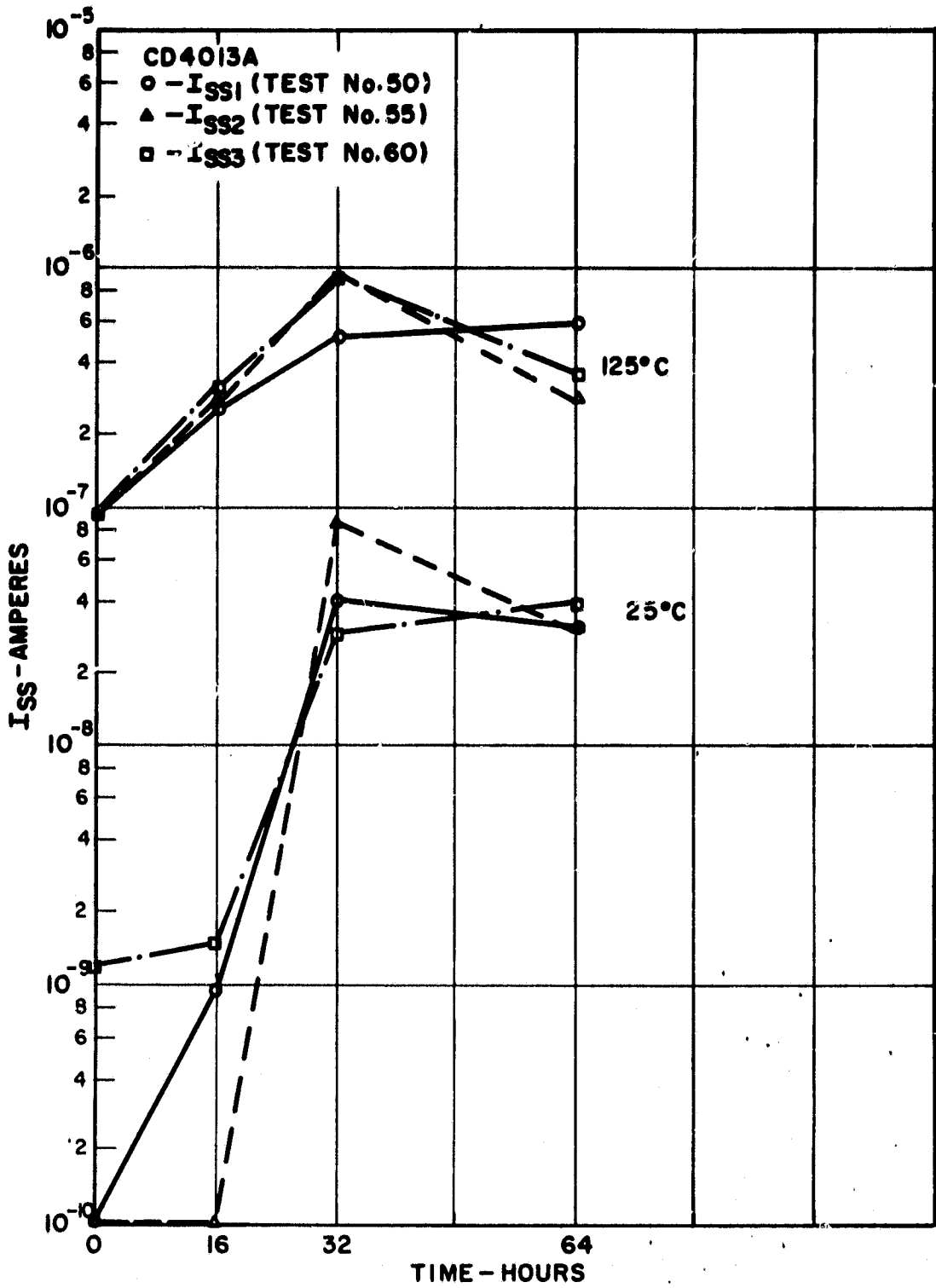
H.V. - High value

Low values were zero



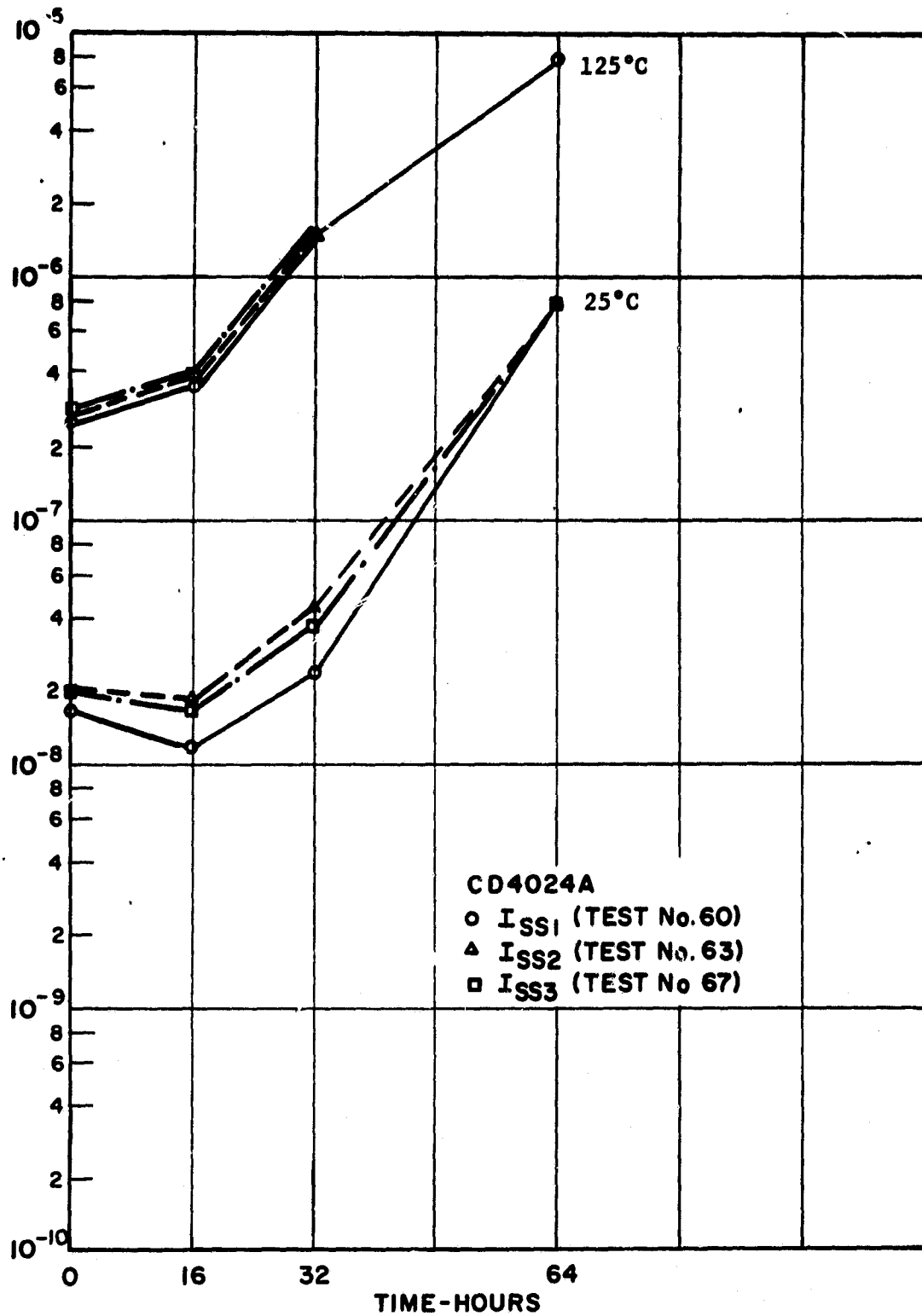
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Fig. 16 - CD4011A; I_{SS} vs time; three-lot average of mean.



92CM-28641

Fig. 17 - CD4013A; I_{SS} vs time; three-lot average of mean. Only one lot was kept on life test to 64 hours. Value of $I_{SS} < 0.1$ nA are plotted on the base line.



92CM-28640

Fig. 18 - CD4024A; I_{SS} vs time; three-lot average of mean. Only one lot was kept on life test to 64 hours.

There are three I_{SS} tests in the M38510/05001 (CD4011A) specifications. The results of all three of these tests were used in the parameter trend tables and graphs. From the M38510/05101 (CD4013A) and M38510/05605 (CD4024A) test results, three I_{SS} tests for each type were selected to avoid presentation of repetitious data. The selected I_{SS} test data indicated the greatest parameter shift. The leakage versus time plot indicates a fair stability for the surviving CD4011A, but shows considerable movement for the CD4013A and CD4024A. The 25°C measurements seems to track the 125°C measurements, indicating that for the purpose of observing leakage shift, both measurement temperatures are equally effective.

Improvement with the Bake

All failures from the 250°C test were subjected to a 200°C, 24-hour stabilizing bake. A large percentage of the failures showed improvement and some recovered completely. The results of this bake are tabulated in Table XXIII. These post bake results are the first indications that the instability of the CMOS microcircuits tested under the high-temperature accelerated conditions is possibly caused by the presence of mobile ions.

Gas Analysis.

Prior to gas analysis, all test devices were subjected to a hermeticity test. All devices were hermetic. Twelve devices (four from each device type) were subjected to gas analysis. The devices were chosen to represent typical failures within each device type. Devices which did not fail were also included. The analysis on these twelve devices was performed by the RCA Methods and Materials Laboratory in Somerville. The summary of this analysis is given in Table XXIV. This table indicates the type of failure for each device: I_{SS} - total leakage, I_i - input leakage, F - functional failure, V_{th} - threshold failure. Although the threshold voltage is not identified as a test parameter by the MIL-M-38510 specifications, it was routinely measured at all measurement points. The threshold tests are included in the table as indicators of device stability under the accelerated testing, but are not considered as one of the criteria for failures.

TABLE XXIII

SUMMARY OF POST BAKE RESULTS

250°C Life Test
200°C 24 Hr Bake

<u>Type/Lot</u>	<u>Hrs. L.T.</u>	<u>No. of Failures</u>	<u>Post Bake</u>		<u>Recovered</u>	
			<u>Improved Amt</u>	<u>%</u>	<u>Amt</u>	<u>%</u>
CD4011A						
5361740	120	17	5	29	10	59
6153050	120	18	8	44	8	44
CD4013A						
5393020	32	11	3	27	7	64
6153080	64	19	8	42	7	37
6123240	32	10	1	10	8	80
CD4024A						
6201060	32	15	8	53	3	20
6202230	64	18	15	83	1	6
6201050	32	11	3	27	1	9

TABLE XXIV - Summary of Gas Analysis (RCA)¹

Device Type	CD4011A					CD4013A					CD4024A			
	4	29	33	56	42	88	10	77	33	62	58	4		
Device Number														
Type of Failure	Iss	Iss, V _{th}	Good	Good	Iss	Iss, I _{IL} /I _{IH} , V _{th}	I _{IL} , I _{IH}	I _{IL} , I _{IH}	Iss, I _{IL} , I _{IH}	Iss	Good	Iss		
Post Bake Result	R	I	-	-	I	I	R	R	NI	NI	-	I		
Constituent ²														
H ₂ %	.15	-	.1	.17	.2	.11	-	.038	830 ppm	.12	.61	.08		
He %	-	-	-	-	-	-	-	-	-	-	-	-		
H ₂ O %	1.2	.15	.33	.06	.29	.47	-	-	.46	.34	.42	3.34		
N ₂ %	96.8	91.5	93.5	89.1	88.8	88.0	93.9	90.5	80.9	82.1	83.46	74.79		
O ₂ %	.16	.26	.32	.15	.22	.17	.18	.15	.17	.10	.1	.36		
Ar %	-	-	.05	-	-	-	-	-	370 ppm	150 ppm	.37	.09		
CO ₂ %	.29	7.6	5.05	9.16	9.8	10.6	5.6	8.77	16.8	15.9	14.33	20.06		
Propane %	.82	.16	-	-	.26	.29	-	-	.67	.58	-	-		
Acetone %	-	.23	-	-	.31	.21	.44	.15	490 ppm	.42	.42	.38		
Ethanol. %	750 ppm	.12	-	-	.15	.12	890 ppm	.4	680 ppm	660 ppm	.06	.08		
Acetylene %	.47	-	-	-	-	-	-	-	.32	.27	-	-		

Notes: 1. Symbols used in this table are defined in Table XXV, page 57.
 2. All measurements shown are in percent by volume unless otherwise noted.

Devices which did not fail are identified with "good". The table further identifies devices which recovered after the bake with R, those which improved with I, and those that did not improve with NI. The constituent analysis is given in percent by volume unless otherwise indicated. In addition to the listed constituents, small amounts (not exceeding 500 ppm) of other organic compounds were found.

Twelve additional devices (four from each device type) were made available to Rome Air Development Center upon request by NASA so that the gas analysis could be performed by RADC. The summary of RADC findings is tabulated in Table XXV. The summary table has only two constituents shown (H_2O and CO_2), which appear to be the two most significant indicators. It can be seen that only those devices which were on the accelerated tests display considerable increase in the amount of H_2O and CO_2 . The amount of water in the CD4011A and CD4013A but not in the CD4024A devices correlates (inversely) to time to failure. The CD4011A failures at the indicated time (64 and 32 hours) amounted to small increases of input leakage. Multiple failures were recorded at 120 hours. The CD4024A's (Nos. 42 and 30), although they had high water-vapor content, did not fail at 32 hours, and for that reason the time is indicated in parenthesis, but the test on the entire lot was discontinued, having accumulated at least 50-percent of failed devices.

It should be noted that there is significant difference in the amount of moisture indicated by the two gas analyses, one performed by RCA and the other by RADC. These variations are attributed to the differences in measurement techniques. RCA measurements are instantaneously done at room temperature; RADC measurements use integration techniques and are conducted at $100^\circ C$.

Chip Analysis

Representative failures from all three device types were opened and failure analysis performed. This analysis was aimed at determining the possible cause for the failures. The summary of this analysis is given in Tables XXVI through XXIX. The tables identify the devices, failure indicators, pins at which problems were detected, and the failure mechanisms.

TABLE XXV - Summary of Gas Analysis (RADC)

Device Type	CD4011A				CD4013A				CD4024A			
	49	50	39	41	23	24	94	95	42	30	19	20
Device Number												
Failure Indicator	C	C	I _{IL} I _{IH}	I _{IL} I _{IH}	C	C	Iss, Vo F	Iss F, V _{th}	Good	Good	Iss	Iss, I _{IL} I _{IH} Vo
Time to Failure, Hrs.	-	-	64	32	-	-	64	16	(32)	(32)	32	64
Constituent			I	I	-	-	I	NI	-	-	I	NI
Water Vapor (%)	.1	.1	7.8	5.9	-	.1	4.5	12.2	12.2	12.0	15.8	11.8
Carbon Dioxide (%)	.3	.3	7.9	7.2	.6	.4	6.3	10.9	7.7	6.0	9.7	7.1

C = Control Device
 F = Functionality
 I = Improved
 I_{IL}/I_{IH} = Input leakage
 Iss = Total device leakage
 NI = No improvement
 R = Recovered after bake
 Vo = Output voltage
 V_{th} = Threshold voltage

TABLE XXVI - CD4011A Failure Analysis

250°C Test

Lot No. Device No.	Failure Indicator	Failure Mechanism and/or Cause
5361740 18	Iss, Vo, Lkg P4,7,10,11	P10 drain to source N channel - minor ionic contamination.
6153050 28	Iss, V, P13-P14 short, Lkg P3,4,7,10,11 - P2,6, 9,13 bias high	P13 - VDD diode shorted. SEM shows cracks at breakdown site. Electrical overstress.
6153050 36	Iss, V, Lkg P3,4,7,10	P channel MOS of P3,4,11 had inversion leakage in 50-100 nanosec range; baking @ 200°C did not improve. Etching oxide cleared leakage. Mobile ion contamination.
6153060 53, 54, 55	Pin 7 open	Vss metal run burned open. Latch during life.

Iss - Leakage into V_{DD} pin.

Vo - Output voltage

Lkg - Leakage into other than V_{DD} pin

TABLE XXVII - CD4013A Failure Analysis

250°C Test

Lot No. Device No.	Failure Indicator	Failure Mechanism and/or Cause
6123240 7	Iss, Lkg 7,8,9	Leakage on P9 transmission gate to VDD = 100mA cleared with oxide etch. Mobile ion contamination.
6153080 89	-	Unit in carrier backwards.
6153080 90	Iss, V _{th} (P), Lkg, P1 2,7,12,13	Heavy invers. - 5uA plus, VDD to Vss diodes cleared with aluminum etch, probably inversion where metal run was over oxide.

Iss - Leakage into VDD pin

V_o - Output voltage

Lkg - Leakage into other than VDD pin

V_{th} - Threshold voltage

TABLE XXVIII - CD4024A Failure Analysis

250°C Test

Lot No. Device No.	Failure Indicator	Failure Mechanisms and/or Cause
6202230 2	Iss, V _o , V _{th} (P), P14 Lkg. P3 Lkg with clock low = 130uA high = 10uA	P3 - VDD diode. Leakage cleared with Al etch. P3 N&P MOS source to drain. Leakage cleared with Al etch + 200°C bake 16 hr. Mobile ion contamination.
6202230 11	Iss, V _o , V _{th} (P) Leakage P7,14 P3 lkg. during toggle switch	Vss to VDD diode 1uA inversion leakage + 4V breakdown. Bake increased inversion to 2.5uA. Leakage cleared with oxide etch, Mobile ion contamination.
6201060 26	Iss, Lkg. P14 - Low Breakdown, 1.8V, P4,P5 Lkg during 10V pulse test.	P5, drain to source, N channel 10uA @ 20V cleared with bake. Mobile ion contamination.
6201060 27	Iss, Pulse test. P1 - IDD = 2.4mA	P1 and P2 P channel source to drain = 20uA. Inversion leakage cleared with 200°C bake. Mobile ion contamination
6201050 51	Iss, V _o , V _{th} (P), Lkg. P7, P14	Carrier insert had melted. Failure analysis halted.

Iss - Leakage into VDD pin

V_o - Output voltage

Lkg - Leakage into other than VDD pins

V_{th} - Threshold voltage

TABLE XXIX - CD4013A Failure Analysis

200°C Test

Lot No. Device No.	Failure Indicator	Failure Mechanism and/or Cause
5393020 334	Continuity Fail. P1,P2 - Short P7 Open, P12,P13 - Short.	Multiple sites of large localized current between P2 and P12. Drains + Vss. Vss metal run buried open. Cause: Electrical overstress during life.
5393020 335	Same as 334	Same as 334
5393020 336	P2, P12 short. P7 Open	Same as 334

SECTION VIII

CONCLUSIONS

The results of accelerated testing of CMOS microcircuits which had been screened in accordance with Table II of MIL-M-38510 detail specification for class A devices, lead to the following conclusions:

1. The applicability of accelerated life tests at 250°C and 200°C as accurate predictors of CMOS device reliability at the use temperature of 125°C has not been experimentally verified because of insufficient data at 125°C after 20,000 hours of testing.
2. The 250°C test temperature is not practical because:
 - a) Deterioration of devices at this temperature is too rapid to permit an accurate determination of the failure distributions under the real-life manufacturing environment.
 - b) Test facilities are costly to maintain.
 - c) Changes in materials used in test facilities at this temperature introduce errors and uncertainties that are impossible to control.
3. The "infant mortality" or "freak" distribution extends beyond 1000 hours in the 125°C accelerated tests. Therefore, the 1000-hour, 125°C life tests, as specified in MIL-M-38510 detail specifications, due to the combination of test conditions, the acceptance criteria, and the inadequacy of the burn-ins, tend to reject lots on the basis of the "infant mortality" failures. Under those circumstances it is a poor predictor of the reliability of CMOS microcircuit devices.
4. The complexity of the CMOS microcircuits has been observed to influence the time-to-failure of a device.
5. Leakage total (I_{SS}) and input (I_{IH}/I_{IL}) was the preponderant failure mode. Leakage failures recovered through baking.

6. Dependence of time-to-failure upon moisture content could not be verified.
7. The activation energies between 250°C and 200°C were estimated to be as follows: for CD4011A, 1.35eV; for CD4013A, 1.25eV; and for CD4024A, 1.0eV. Insufficient data from the 125°C test cell prevented a more accurate three-point verification of these estimated activation energies.
8. Development of accelerated life-test specifications that could be equally effective in predicting reliability for all CMOS microcircuits could not be accomplished for the following reasons:
 - a) Insufficient data at 125°C test temperatures.
 - b) Varying complexity of devices apparently influenced the results of testing.
 - c) Variation of the activation energy from device type to device type.

SECTION IX
RECOMMENDATIONS

On the basis of the test results and the conclusions reached, a program for the development of the accelerated life-test conditions can be recommended along the following guidelines:

Recommendations

It is essential for the development of the accelerated test specifications to establish correlation experimentally between the failure distributions at the use temperature (125°C) and the temperature to be used for the accelerated test. Testing beyond 20,000 hours at 125°C is, therefore, recommended. Should the failure distributions at 125°C correlate with those at 200°C, a two-test-point specification to control both the freak and the main distributions ought to be considered. Should the failure distributions be significantly different from those at 200°C, other test temperatures between 125°C and 200°C must be investigated.

The relationships between the complexity of microcircuits and their reliability needs to be investigated in more detail. Various life-test conditions may be required, based on microcircuit complexity groups. As the complexity of a microcircuit increases, there is less certainty as to the state in which a complex device finds itself when fixed bias is used. Therefore, dynamic versus fixed bias-life test conditions need to be explored. The use of non-burned-in devices in life testing investigations should be helpful in assessing the effectiveness of burn-ins in removing freak distributions. The present limits for input leakage (1 nA for an individual input pin) at downtime measurements in life testing should be relaxed in order to overcome mild instabilities that may occur in the device, in the environment, or in the testing system. A 10X initial limit is suggested for the individual input pins and a 5X initial limit is suggested for the ganged input-pin measurements.

APPENDIX

84

ACCELERATED LIFE TESTING EFFECTS ON
CMOS MICROCIRCUIT CHARACTERISTICS

Selection of an optimum deposition and combination of protective layers through testing and evaluation of Silicon Nitride (SiN_x)

Phase IV Report
November 1977 to April 1979

June 1979

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ACCELERATED LIFE TESTING EFFECTS ON
CMOS MICROCIRCUIT CHARACTERISTICS

PHASE IV REPORT

CONTRACT NAS8-31905

I. INTRODUCTION

The results of Phase I and Phase II of this contract (250°C and 200°C accelerated tests) as well as work done by RCA's various activities in the field of reliability improvement suggest that reduced longevity of the CMOS microcircuits under high-temperature accelerated testing is primarily due to contaminants external to the chip. The presence of small amounts of moisture enhances the mobility of the contaminant ions, thereby contributing to increased leakage currents and changes in other device characteristics, such as threshold and output voltage, under the high-temperature accelerated testing. Phase IV introduces modifications and additions to the present process of making CMOS microcircuits which are designed to provide protective layers on the chip to guard against moisture and contaminants.

II. OBJECTIVES

1. The improvement of the Class A CMOS microcircuit high-temperature accelerated-test characteristics through deposition of silicon nitride protect layers.
2. The selection of the optimum process for further evaluation under high-temperature accelerated-test conditions.

III. THE PROCESS

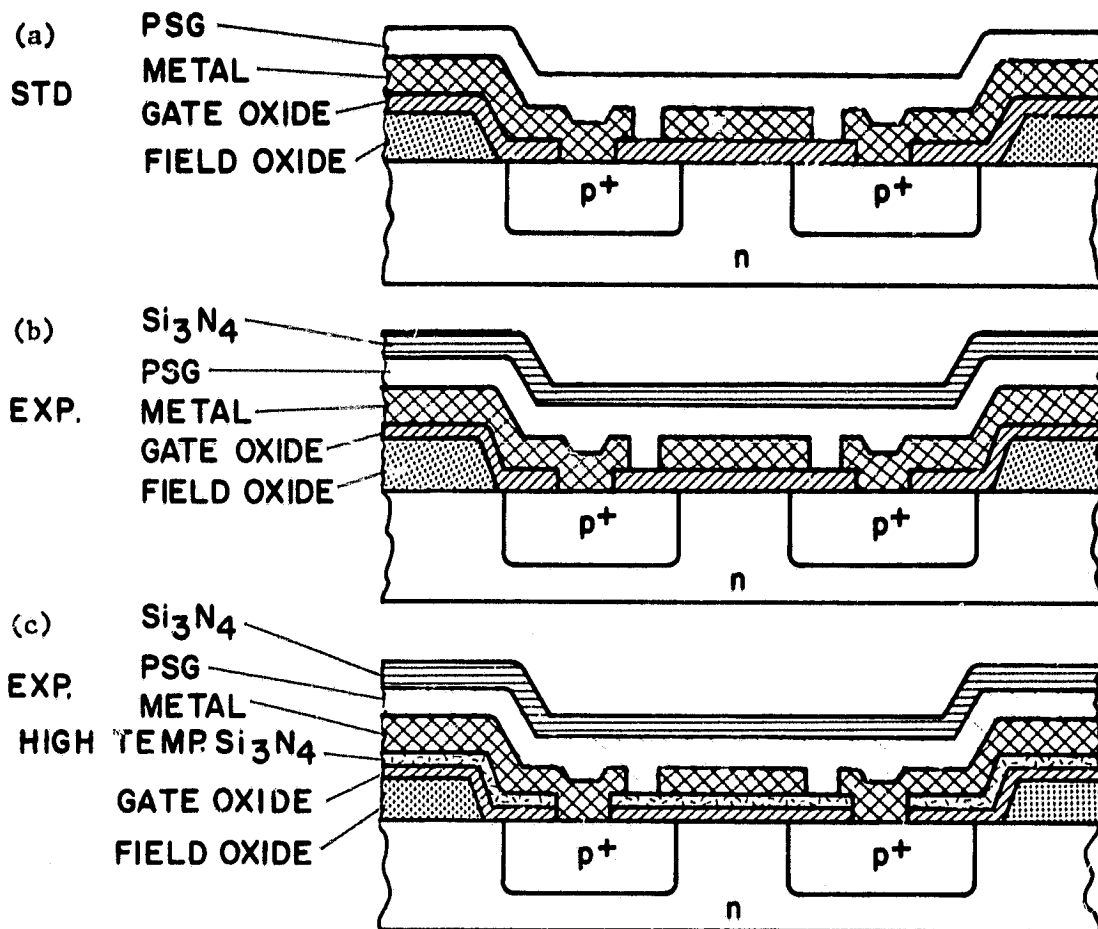
The standard wafer-manufacturing process was modified by the introduction of two distinctly different silicon nitride (Si_3N_4) protect layers. These two kinds of Si_3N_4 layers are distinguished by the method of deposition and, therefore, resultant characteristics.

The high-temperature Si_3N_4 layer is deposited in a furnace at 800°C . This method of deposition results in a dense layer which is impervious to contaminants, has a slow etch rate, and which provides a good barrier to sodium. The deposition of the layer over the field oxide presents few problems. When the layer is deposited over the channel oxide, its thickness must be minimized ($175 - 200\text{\AA}$) to prevent the formation of a metal-to-channel oxide interface and the possibility of accumulation of undesirable charges. Fig. 1(c) shows the location of this layer.

The low temperature Si_3N_4 layer is plasma deposited after the metalization, at 310°C , a temperature low enough to prevent alloying of aluminum metal into the silicon. This type of deposition results in a less dense layer with a higher etch rate. The layer is deposited over the entire chip and is made relatively thick ($3\text{k}\text{\AA}$ to $10\text{k}\text{\AA}$) in an attempt to make it impervious to contaminants, Figs. 1(b) and (c). The PSG (phosphorous silica glass) layer standard in current RCA processing is retained with the idea that it may still serve the useful function of gettering for those contaminants that might be trapped under the protect layer.

VI. DEVICE SELECTION

The simplicity of the CD4007A device type was the compelling reason for choosing it as the vehicle for this experiment. A wealth of life-test information is also available for this device type. The schematic diagram of Fig. 2 shows the internal connections of the CD4007A; the easy accessibility to individual transistors should greatly facilitate the analysis of failures resulting from subsequent testing and evaluation.



92CS-33060

Fig. 1 - Deposition of layers on p-channel transistor.

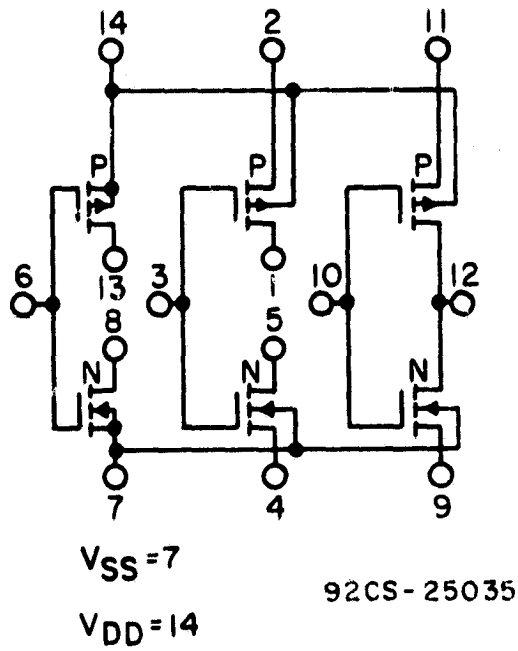


Fig. 2 - Schematic diagram for CD4007A. Dual complementary pair plus inverter.

V. DEVICE FABRICATION

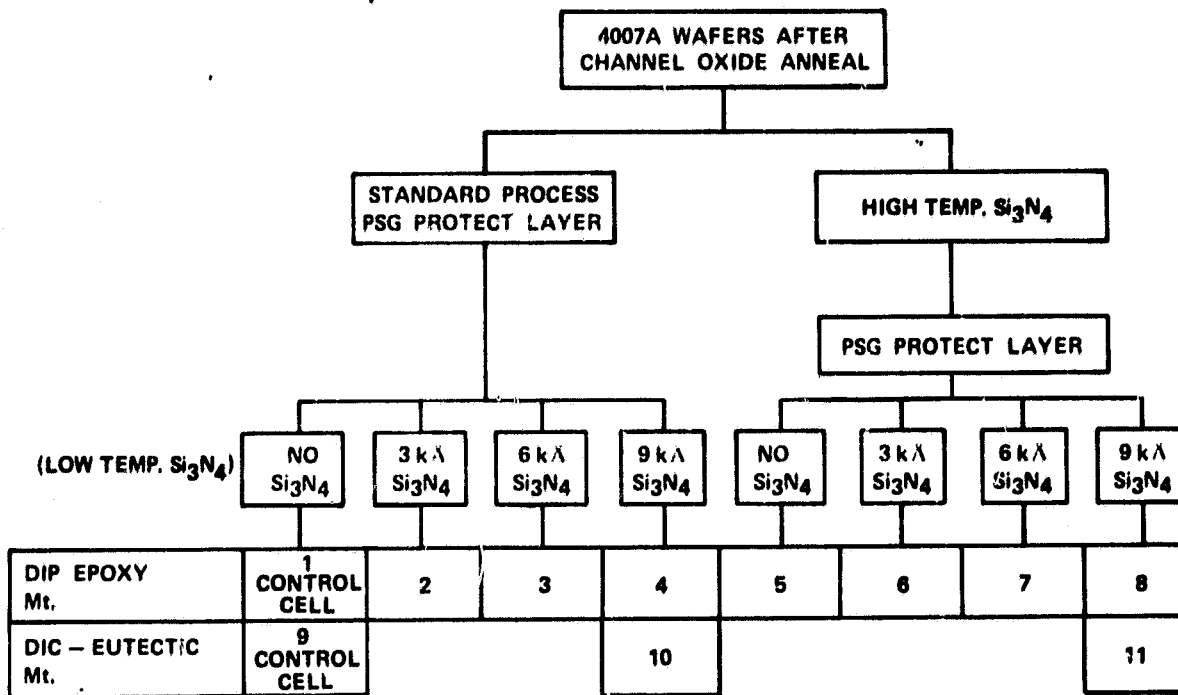
The experimental cell matrix was developed as shown in Fig. 3. Twenty-four wafers were processed by means of the standard RCA process for fabricating commercial CMOS IC's through channel-oxide deposition. At this point, the wafer lot was divided into two parts. One half received a deposition of high temperature Si_3N_4 over the field and the gate oxides. Then the entire lot was put through standard processing up to the final step of low-temperature Si_3N_4 deposition. At this step, eight cells (1 through 8) were created on which the low temperature Si_3N_4 was deposited in various thicknesses. Cell No. 1 was designated as the control cell and received no Si_3N_4 deposition. Cells No. 2, 3, and 4 had only the low temperature Si_3N_4 deposited. Cell No. 5 had the high temperature Si_3N_4 only. Cells No. 6, 7, and 8 had both the high temperature and the low temperature Si_3N_4 deposition. After the wafer processing had been completed, cells No. 1, 4, and 10 were further divided, so that one half of each could be assembled with eutectic mounts in ceramic packages. Consequently cells No. 9, 10, and 11 are eutectically mounted devices from cells No. 1, 4 and 8, respectively.

The wafers were circuit probed with high resultant yields, which is a good indicator of the manufacturability of the process. For comparison, the circuit probe yields for the CD4007A were:

For the 1977 year, 80 to 85%

For the Si_3N_4 experiment, 82%

The control cell (No. 1) and the test cells (Nos. 2 through 8) were assembled in standard plastic dual-in-line packages. The pellets were mounted with epoxy used in the RCA CD4000 commercial series. The Novolac plastic package is thought to accentuate problems that might be encountered in subsequent testing, thereby reducing the duration of tests. The assembled devices were screened to commercial specifications to net 60 good devices per cell for further evaluation.



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Fig. 3 - Experimental cell matrix.

The devices in test cells Nos. 9, 10 and 11 were to be eutectically mounted in ceramic (DIC) packages so that they could be tested under high-temperature accelerated-test conditions. These three cells represent those test cells appearing as the last line in the experiment matrix of Fig. 3.

VI. TEST AND EVALUATION

The evaluation of the effectiveness of the Si_3N_4 protect layers as the barriers to contaminants required the type of testing that provides sufficient stressing, particularly in two areas: the high-temperature and high-humidity environment. Three tests were used to achieve this type of stress:

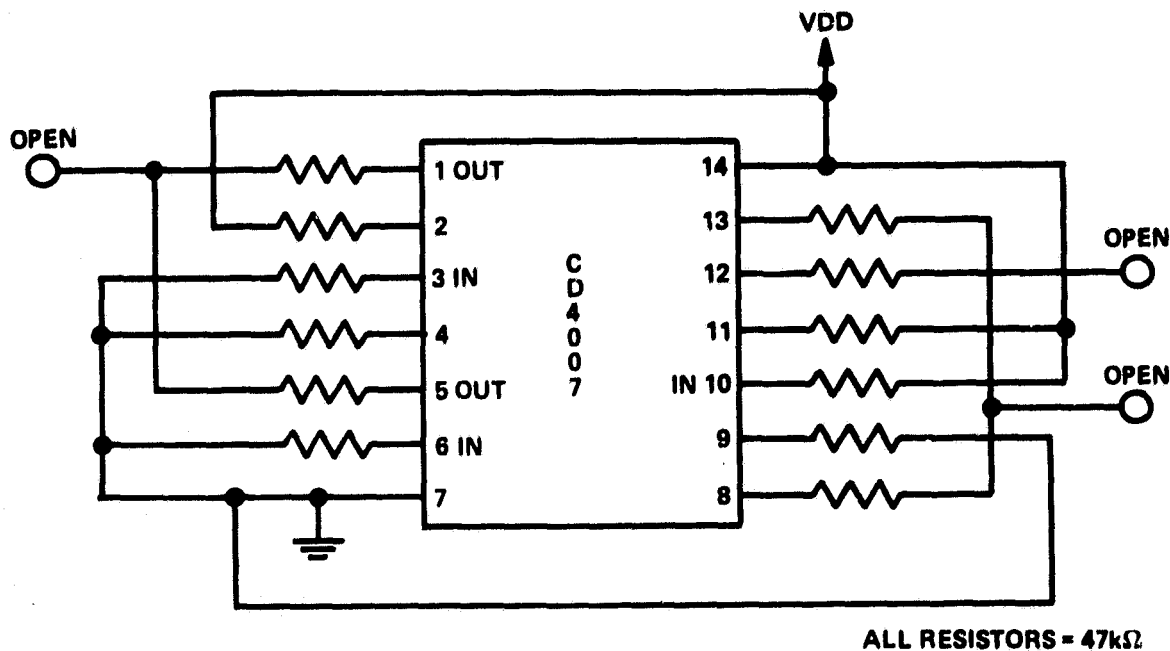
1. 200°C bias/temperature test
2. 150°C bias/temperature test
3. 85°C/85% relative-humidity, bias/humidity tests.

All tests were conducted at 12.5 V dc. The circuit bias arrangement used was the standard burn-in bias configuration shown in Fig. 4. Each test cell from No. 1 to No. 8 was tested in accordance with the schedule of Fig. 5. The electrical measurements were taken initially and at each down-time as indicated for tests 1, 2, and 3. The anticipated end-of-test time for each test is also shown in Fig. 5 as the last down-time.

It was thought, from experience, that all test cells would have generated a sufficient number of out-of-specification devices at each end-of-test time to provide the basis for comparison among the test cells. However, it was found during the actual testing that the longevity of the test devices was underestimated. Neither 240 hours at 200°C nor 1152 hours at 150°C were producing enough out-of-specification devices for conclusive evaluation. Because of time and equipment limitations it was then decided to continue beyond the anticipated end-of-test time with the 200°C bias-temperature test only. The 200°C test in actuality had to be extended to 500 hours and eventually to 768 hours before a conclusive evaluation could be done.

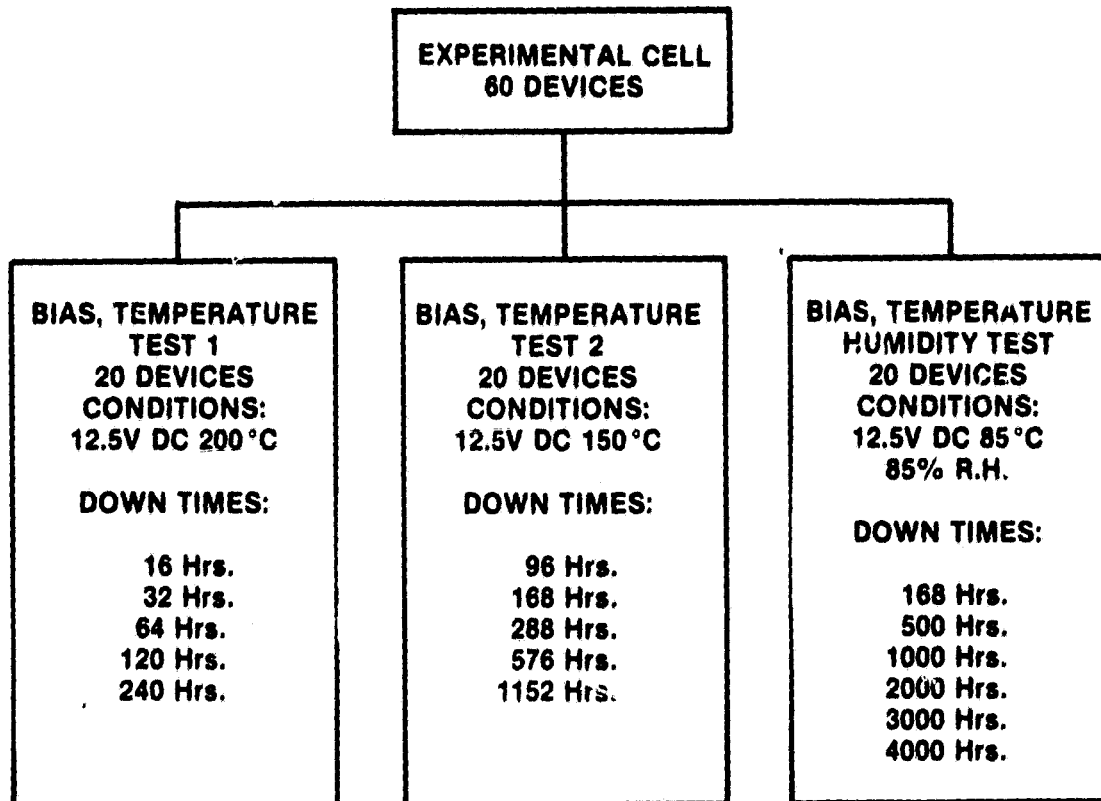
The test parameters and the limits used in testing cells 1 through 8 were those of the standard commercial device specifications. The use of specifications more relaxed than those of the MIL-M-38510 detail specifications was dictated by the need to detect gross differences among the test cells rather than differences resulting from subtle process variations. Table I gives the commercial specification test limits.

One group of devices, Cells 9, 10 and 11 were designated to be tested to MIL-M-38510 detail specifications, Table II. These devices were assembled in ceramic packages with eutectic mounts and tested with a 200°C bias/temperature test so that the test results could be compared to those obtained in Phase II. These devices were represented by the



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Fig. 4 - Burn-in diagram.



ALL DEVICES AT EACH DOWN TIME ARE CRITICIZED TO COMMERCIAL LIMITS

Fig. 5 - Testing and evaluation of each cell.

TABLE I - Commercial Specification Test Limits

<u>Parameter</u>	<u>Test Condition</u>	<u>Limits</u>	
		<u>min.</u>	<u>max.</u>
Quiescent device current, I_L	$V_{DD} = 10V$		1 mA
Output voltage, low level, V_{OL}	$V_{DD} = 10V$		0.01V
Output voltage, high level, V_{OH}	$V_{DD} = 10V$	9.99V	
Noise immunity	$V_{DD} = 10V$		
Low V_{NL}	$V_o = 7.2V$	3V	
High V_{NH}	$V_o = 2.9V$	3V	
Output drive current	$V_{DD} = 10V$		
n-channel I_{DN}	$V_i = V_{DD}, V_o = 0.5$	1 mA	
p-channel I_{DP}	$V_i = V_{SS}, V_o = 9.5$	-0.55 mA	

three test cells Nos. 9, 10, and 11. Test-cell No. 10 had the low temperature Si_3N_4 layer only while test-cell No. 11 had both the low-temperature and the high-temperature Si_3N_4 layers. Test cell No. 9 was accidentally lost during handling.

The electrical measurements on this group of devices were performed by using the test programs based on the MIL-M-38510 detail specifications. This method of testing provided test results directly comparable to earlier accelerated-test evaluations of CMOS microcircuits to the MIL-M-38510 specifications. It also provided a preview of the capability of the eutectic-mount and Si_3N_4 protect-layer combination under high-temperature accelerated-test conditions.

VII TEST RESULTS

The test matrix in this experiment was designed so that the analysis of the test results could be conducted in steps. At first a determination must be made as to whether there is an improvement in either of the two test groups over the control cell. If there is an improvement in more than one cell, a comparative evaluation among the test cells must be made to determine which of the test cells possesses the best characteristics. The improvement must be demonstrated in both the high-temperature and high-humidity environments. The test results are summarized in Table III.

The 150°C bias/temperature test can be eliminated from consideration immediately because the control cell has not produced a single out-of-specification device in this test. The results of the other two tests, the 200°C bias/temperature and the 85°C/85% relative-humidity tests, can be analysed by the application of the three regions in the life of a device: The "infant-mortality" region, the "constant-failure-rate" region, and the "wear-out" region.

None of the test devices has been burned-in; consequently, the devices which exceeded the specification limits during the first 16 hours in the 200°C test as well as the out-of-specification devices occurring within the first 168 hours in the 85°C/85% relative-humidity test could be attributed to the infant mortality. The constant-failure-rate region appears to fall between the 16-hour point and the 500-hour point in the 200°C test. At the 500-hour point, devices begin exceeding the specification limits in numerous cells,

TABLE II (continued)

TABLE III. Group A Inspection for device type 01 - Continued.

Symbol	MIL-STD-883 method	Terminal conditions and limits											Test Limits										
		Case A, C, D											Subgroup 9 T _A = 25°C		Subgroup 10 T _A = 125°C		Subgroup 11 T _A = -55°C						
		Test No.	2aY	2a5	2A	2b5	2bY	1A	V _{SS}	1bY	3b5	3A	3a5	3Y	1aY	V _{DD}	14	Meas. terminal	Min	Max	Min	Max	Min
t _{PLH}	3003	44	(5)	5.0 V	GND	GND	(1)	IN	GND	(13)	GND	5.0 V		(8)	5.0 V		1A to 1aY	110	165	110	165	110	165
t _{PLH}	(Fig. 6)	45			IN	GND		GND									2A to 2aY	110	165	110	165	110	165
t _{PLH}		46			GND	GND		IN									3A to 3Y	170	255	170	255	170	255
t _{PHL}		47			GND	GND		IN									1A to 1aY	170	255	170	255	170	255
t _{PHL}		48			IN	GND		GND									2A to 2aY	170	255	170	255	170	255
t _{PHL}		49			GND	GND		IN									3A to 3aY	170	255	170	255	170	255
t _{THL}	3054	50			GND	GND		IN									1aY	240	360	240	360	240	360
t _{THL}	(Fig. 6)	51			IN	GND		GND									2aY	240	360	240	360	240	360
t _{THL}		52			GND	GND		IN									3Y	240	360	240	360	240	360
t _{TLH}		53			GND	GND		IN									1aY	160	240	160	240	160	240
t _{TLH}		54			IN	GND		GND									2aY	160	240	160	240	160	240
t _{TLH}		55			GND	GND		IN									3Y	160	240	160	240	160	240

NOTES:
 A. Plus not designated may be "high" level logic, "low" level logic or open. Exceptions are as follows: V_{IC}(POS) tests, the V_{SS} terminal shall be open;
 B. VIC(NEG) tests, the V_{DD} terminal shall be open; ISS tests, the outputs shall be open.
 C. I_{OH1} = 0.1 mA at 25°C; 0.1 mA at 125°C; -0.1 mA at -55°C.
 D. I_{OH2} = 0.30 mA at 25°C; -0.21 mA at 125°C; -0.375 mA at -55°C.
 E. V_{IH1} = 3.95 V at 25°C; 3.85 V at 125°C; 4.05 V at -55°C.
 F. V_{IH2} = 10.25 V at 25°C; 10.0 V at 125°C; 10.5 V at -55°C.
 G. I_{OL1} = .23 mA at 25°C; .23 mA at 125°C; .23 mA at -55°C.
 H. I_{OL2} = 600µA at 25°C; 400 µA at 125°C; 750 µA at -55°C.
 I. V_{IL1} = 0.9 V at 25°C; 0.65 V at 125°C; 0.95 V at -55°C.
 J. V_{IL2} = 2.25 at 25°C; 1.95 V at 125°C; 2.40 V at -55°C.
 K. Terminals in parentheses are connected together as indicated by the included number.
 L. See 4.4.1(c).
 * indicates the device manufacturer may, at his option, measure I_{PL} and I_{PH} at 25°C for each individual input or measure all inputs together.

TABLE III - Test Result of Cells No. 1 Through 8; Number of Out-of-Specification Devices

Test Description	Cell No.	Standard Process With Low Temp. Si ₃ N ₄				High Temp. Si ₃ N ₄ Layer With Low Temp. Si ₃ N ₄			
		1	2	3	4	5	6	7	8
	Si ₃ N ₄								
	Thickness	0A	3kA	6kA	9kA	0A	3kA	6kA	9kA
	Sample Size	20	20	20	18	20	20	20	19
	<u>Downtime Hours</u>								
200°C	16	0	0	0	2	0	0	0	0
Bias/Temperature Test	32	0	0	0	0	0	0	0	0
	64	0	0	2	0	0	0	0	0
	120	0	0	1	0	0	0	0	1
	240	0	0	0	0	0	0	0	0
	500	1	0	4	0	8	0	5	3
	768	14	18	10	16	12	17	12	12
	Cumulative	15	18	17	18	20	17	17	16
	<u>Sample Size</u>	20	20	20	20	18	19	16	20
	<u>Downtime Hours</u>								
150°C	96	0	0	0	0	1	1	2	0
Bias/Temperature Test	168	0	0	0	0	0	0	0	0
	288	0	1	0	0	0	0	0	0
	576	0	0	1	0	0	0	1	0
	1152	0	0	1	0	0	0	0	0
	Cumulative	0	1	2	0	1	1	3	0
	<u>Sample Size</u>	19	20	20	20	19	20	18	20
	<u>Downtime Hours</u>								
85°C/85% R.H.	168	1	0	0	0	0	0	0	0
Bias/Humidity Test	500	0	0	0	0	1	0	0	0
	1000	0	0	1	0	0	0	0	0
	2000	0	2	0	0	2	0	0	0
	3000	0	1	0	0	3	1	2	3
	4000	5	7	1	1	1	6	0	1
	Cumulative	6	10	2	1	7	7	2	4

an indication of the onset of the wear-out region. The test data at 768 hours clearly indicates that the wear-out region for all the cells has been reached before that time. Because of the absence of out-of-specification devices in the control cell within the constant-failure-rate region, the wear-out region must be used as the criterion for comparative evaluation of cells. By using that criterion, cells 2, 4, and 6 appear as having demonstrated characteristics equal to or better than those of the control cell. None of these cells has had an out-of-specification device in the constant-failure-rate region, up to and including the 500-hour point. The two out-of-specification devices in cell No. 4 are attributed to infant mortality. The control cell had an out-of-specification device at the 500-hour point. The wear-out region for these test cells lies somewhere between 500 hours and 768 hours. The rate of deterioration for the devices in this region is probably similar for all cells, as can be judged by the recorded number of out-of-specification devices at the 768-hour point.

Similarly, the onset of the wear-out region in the 85°C/85% relative-humidity test, at least for some cells, is evidenced at the 4000-hour point. From among the test cells identified earlier, only cell No. 4 remains in the contest with the control cell because of the condition that a cell must demonstrate improvement in both the 200°C and 85°C/85% relative-humidity test to be in contention. At the 4000-hour point cell No. 4 has had one out-of-specification device versus five such devices (exclusive of one early out-of-specification device) in the control cell. This result tends to indicate the possibility that the heavy coat (9kÅ) of low-temperature Si_3N_4 is presenting a barrier to moisture. The group with two Si_3N_4 layers did not do as well, in general, suggesting that perhaps the technique of depositing the thin high-temperature Si_3N_4 layer may need further perfecting.

Test cells No. 10 and 11 were tested at 200°C and evaluated to the MIL-M-38510 detail specifications. At the 16-hour down time, both test cells had produced devices out of specification in leakage (I_{SS}); test cell No. 11 has had devices with out-of-specification leakage (I_{SS}), and with p-threshold voltage deteriorating to 0.5 to 0.9-volt levels. One device had zero p-threshold voltage at the 16-hour test point.

Table IV summarizes the number and kind of out-of-specification devices which occurred in test cells No. 10 and 11. The threshold problems have occurred in the same devices that failed leakage tests. The early problems of the kind that were observed indicated the possible presence of mobile ions. This possibility was checked in both test cells by baking devices at 150°C for 24 hours. A complete recovery in some cases and partial recovery in many others was observed. The bias/temperature test was repeated for another 16 hours, and a recurrence of excessive I_{SS} and V_{TH} problems was observed. The threshold deterioration in test cell No. 11, which has both Si_3N_4 layers, is further evidence of the presence of mobile ions in the lot with the high temperature Si_3N_4 layer. The results of this testing do not compare favorably with the results of tests conducted in Phase II of this contract on CD4011A, CD4013A, and CD4024A devices. Due to a large number of failures (40% in one cell and 75% in the other) the test was terminated after 16 hours of testing.

CONCLUSION

The results of the evaluation of the high-temperature and low-temperature Si_3N_4 protect layers conducted within the scope of this effort lead to the following conclusions:

1. The application of the Si_3N_4 layers in all of the tested combinations failed to lead to a demonstrably conclusive improvement in device reliability characteristics.
2. There is some evidence that a heavy (9kÅ) layer of low-temperature Si_3N_4 presents a barrier to moisture. A further, more detailed study is required for a more conclusive statement.
3. The testing of eutectically mounted devices has not produced a desirable degree of improvement in reliability characteristics.

TABLE IV - Test Results for Eutectically Mounted
CD4007A, Cells 10 and 11

<u>200°C Bias/Temperature Test</u>		
Cell No.	10	11
Sample size	20	20
No. of failures at 16 hours	8	15
Type of failures	I_{SS}	I_{SS} ($V_{th(n)}$, 9 devices)*

*For information only

MIL-M-38510 detail specification does not criticize
for V_{th} . Nine devices had $V_{th(n)} < 1.0V$.